

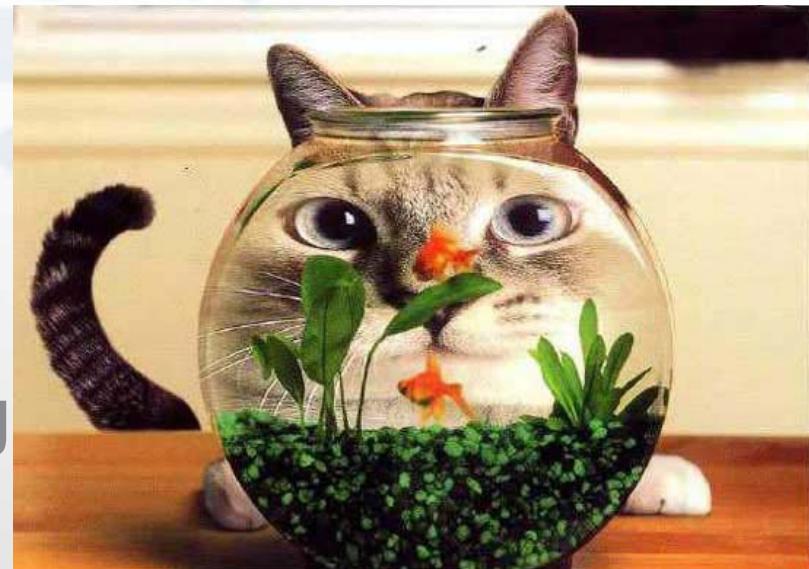
ESI2011: 2nd EIROforum School on Instrumentation

X-ray Optics for Synchrotron Radiation Beamlines

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European Synchrotron Radiation Facility

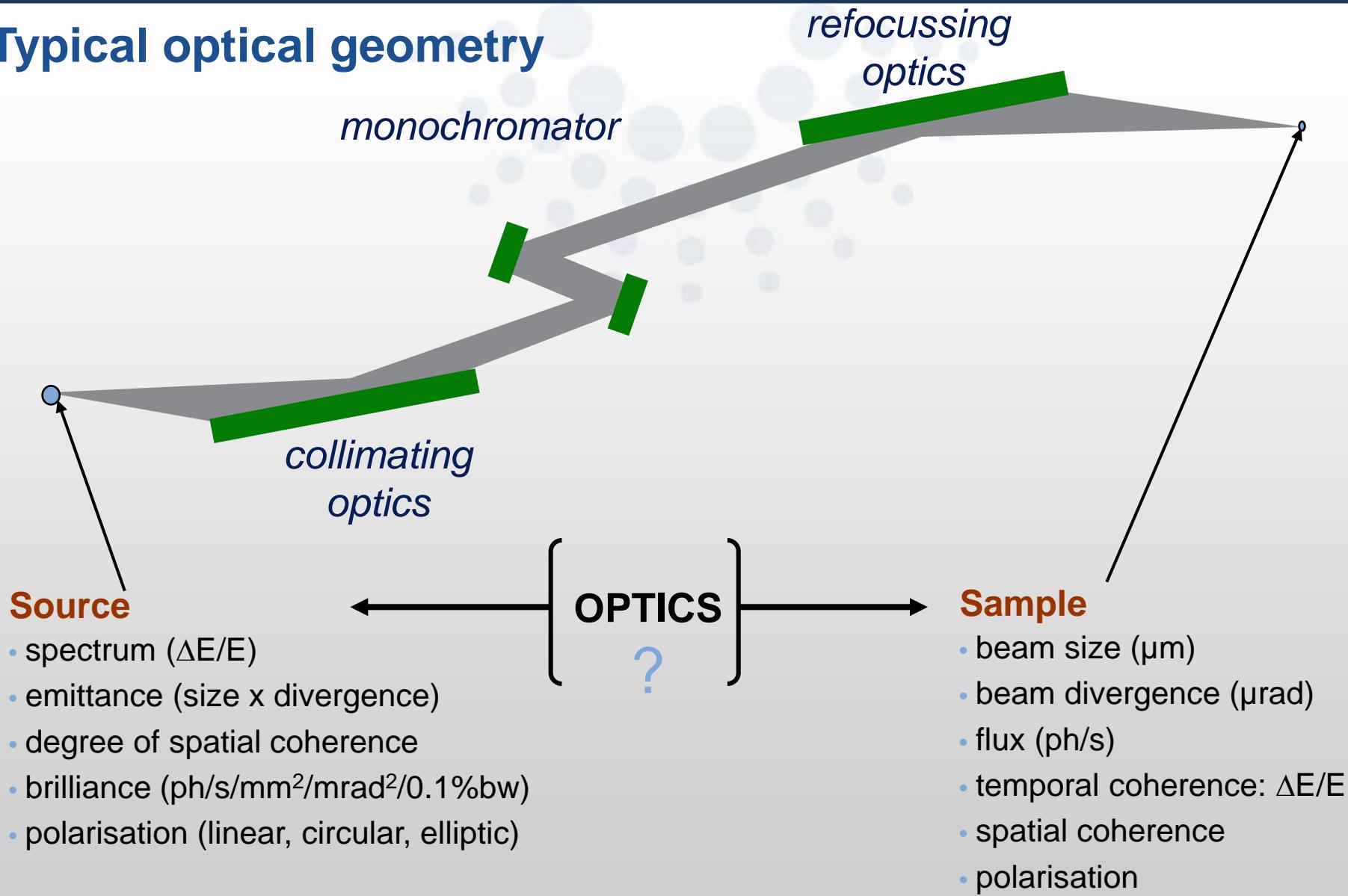
- Introduction
- General X-ray optics
- High heat-load optics
- X-ray micro-/nano-focusing
 - Reflectors
 - Zone plates
 - Refractive lenses
- Summary



Scope:

- Non-exhaustive overview
- Some general X-ray optics – foundation for X-ray focusing
- Primarily ‘hard’ X-ray optics (i.e. photon energies $>2\text{keV}$)
- Slight bias for ESRF applications
- References for further reading

Typical optical geometry

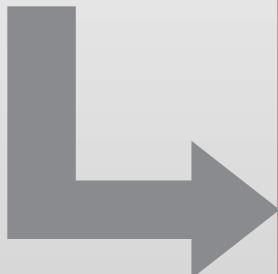


• Tasks:

- *transform beam to obtain the best match to experimental requirements*

• Act upon:

- shape
- wavelength/energy
- divergence
- polarisation



- slits, pinholes
- filters, windows
- mirrors
- beam splitters (crystals)
- monochromators (crystals, multilayers)
- phase plates (crystals, multilayers)
- lenses, zone plates
- combined elements (ML gratings, Bragg-Fresnel-lenses)

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Anna Bertha Röntgen
Taken 1895

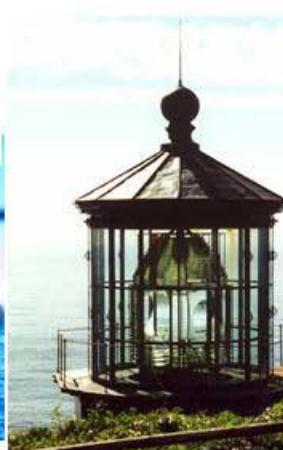


Wilhelm Conrad Röntgen
1845-1923

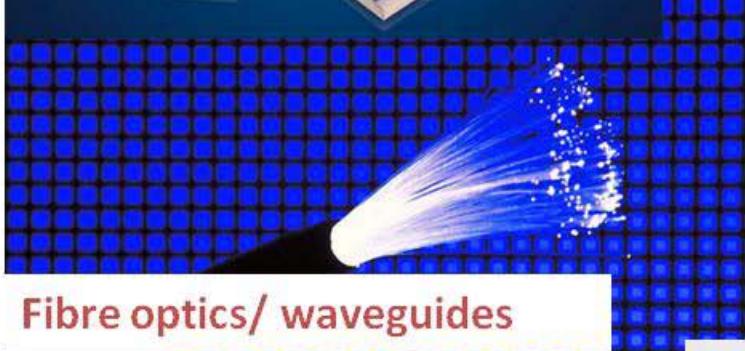
Refractive lenses



Polarising Optics

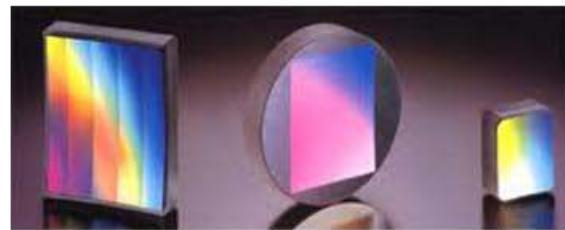


Fresnel lenses



Fibre optics/ waveguides

Diffractive optics



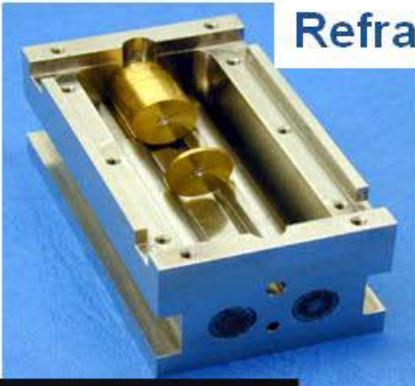
Filters



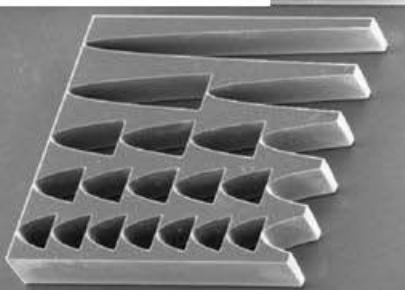
Mirrors



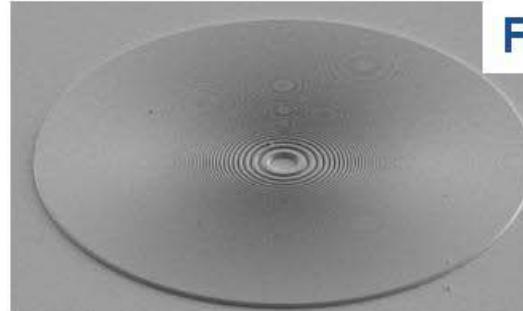
+ interferometers, ...



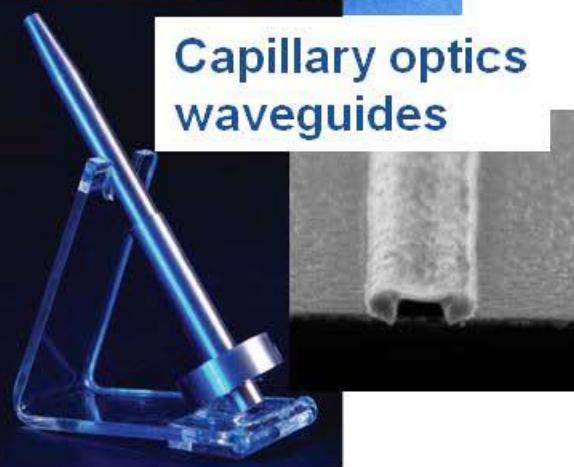
Refractive lenses



Fresnel lenses

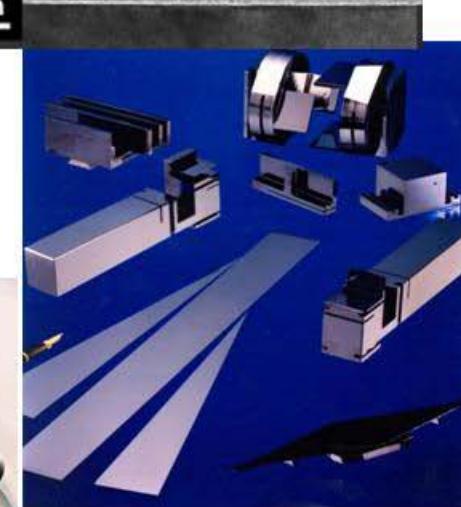


Capillary optics
waveguides

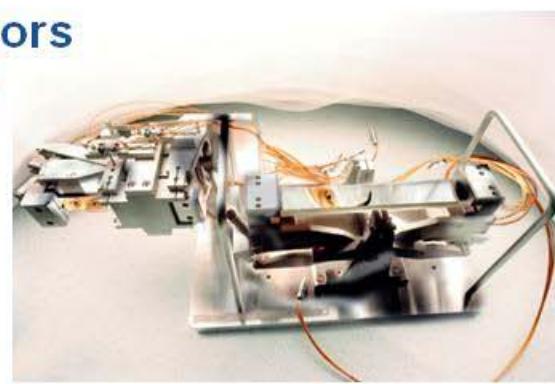
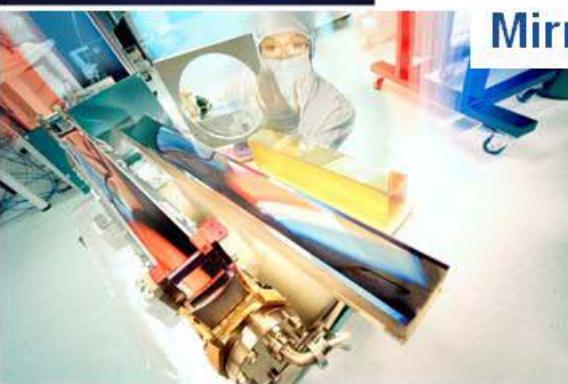


Diffractive optics

20 nm



Filters



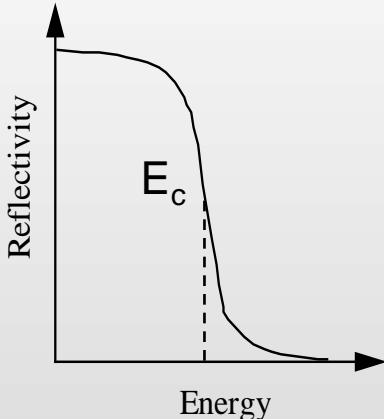
+ polarising optics,
interferometers, ...

“... The refractive index.... cannot be more than 1.05 at most....
X-rays cannot be concentrated by lenses...”

W.C. Röntgen
 Über eine neue art von Strahlen.
 Phys.-Med. Ges., Würzburg, 137, p. 41,
 (1895)
 English translation in Nature 53, p. 274

$$n=1-\delta+i\beta \text{ with } \delta, \beta \lll 1$$

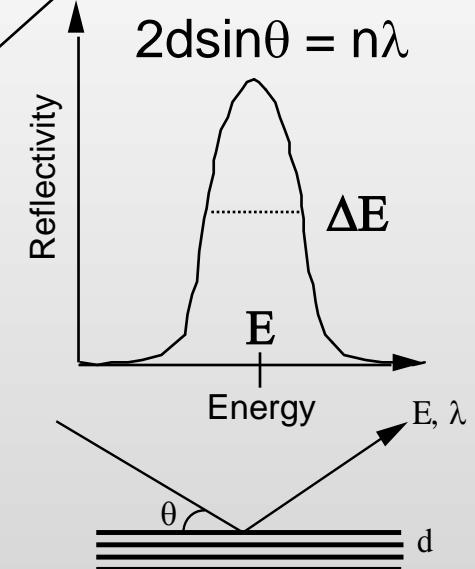
REFLECTION



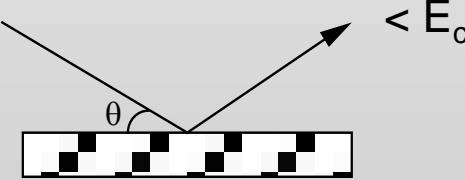
δ (phase-shift), β (absorption), materials
 (and energy) dependent optical constants

- Very weak refraction
- Quite high absorption

DIFFRACTION



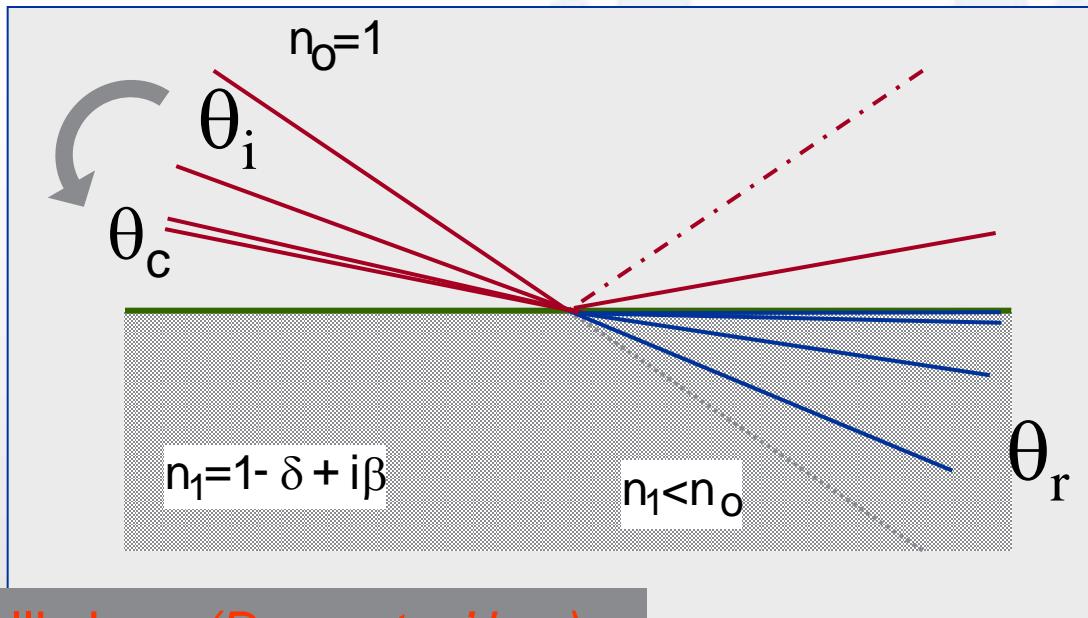
REFRACTION



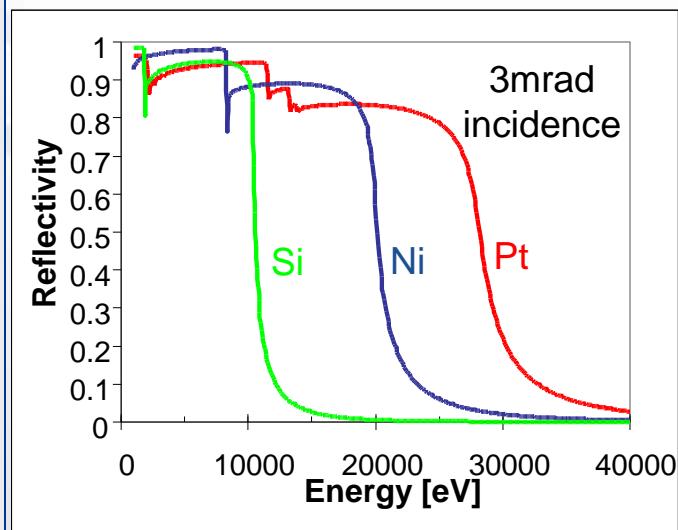
- X-ray mirrors
- Capillaries
- Waveguides

- Refractive lenses

- Crystals & multilayers
- X-ray gratings
- Fresnel zone plates
- Bragg-Fresnel lens



'real' materials



Snell's Law (*Descartes' law*) :

$$n_o \cos \theta_i = n_1 \cos \theta_r$$

for $\delta \ll 1$ and $\beta \ll \delta$

$$\theta_{c[mrad]} E_{c[keV]} = 19.83 \sqrt{\rho_{[g/cm^3]}}$$

$$\theta_c \approx \sqrt{2\delta} \propto \lambda \sqrt{Z}$$

The critical angle for total external reflection.

E=10keV

- Gold 9 mrad
- Nickel 6 mrad
- Silicon 3 mrad

See also: <http://www.coe.berkeley.edu/AST/sxreuv/>

• Deflection

- beam steering (different experiments, Bremsstrahlung)

• Power filter

- lower incident power on sensitive optical components

• Spectral shaper

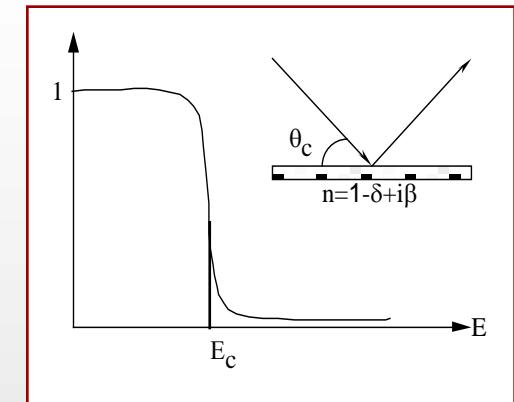
- energy low-pass filter (harmonic rejection)
- mirror+filter = spectral window

• Focusing

- wiggler & bending magnet : spherical, cylindrical, and toroidal mirrors
- microscopy & microprobe : source demagnification (ellipsoidal mirror, KB

• Collimation

- parabolic mirror : matching the monochromator angular acceptance with the beam divergence



J. Susini, Optical Engineering, 34(2), (1995)

- Typical Requirements

- *micro-roughness* < 3 Å rms and *slope error* ~1 µrad rms for blur -10% source size
 - Ultra-precise shaping, figuring and super-polishing
 - Very accurate and stable mechanical mounting, bending mechanisms, UHV environment
 - Efficient cooling scheme

- Technically limiting parameters

- gravity sag

$$\Delta_g \propto \frac{5g}{32} \frac{L^3}{t^2} \frac{\rho}{E}$$



- vibration

$$f_o \propto \sqrt{\frac{E}{\rho}}$$

- thermal deformation

$$\Delta_t \propto \frac{\alpha}{\kappa} P_s$$

- bending

$$F_b \propto E \frac{\alpha}{\kappa} P_t w t^3$$

+

“Polishability”

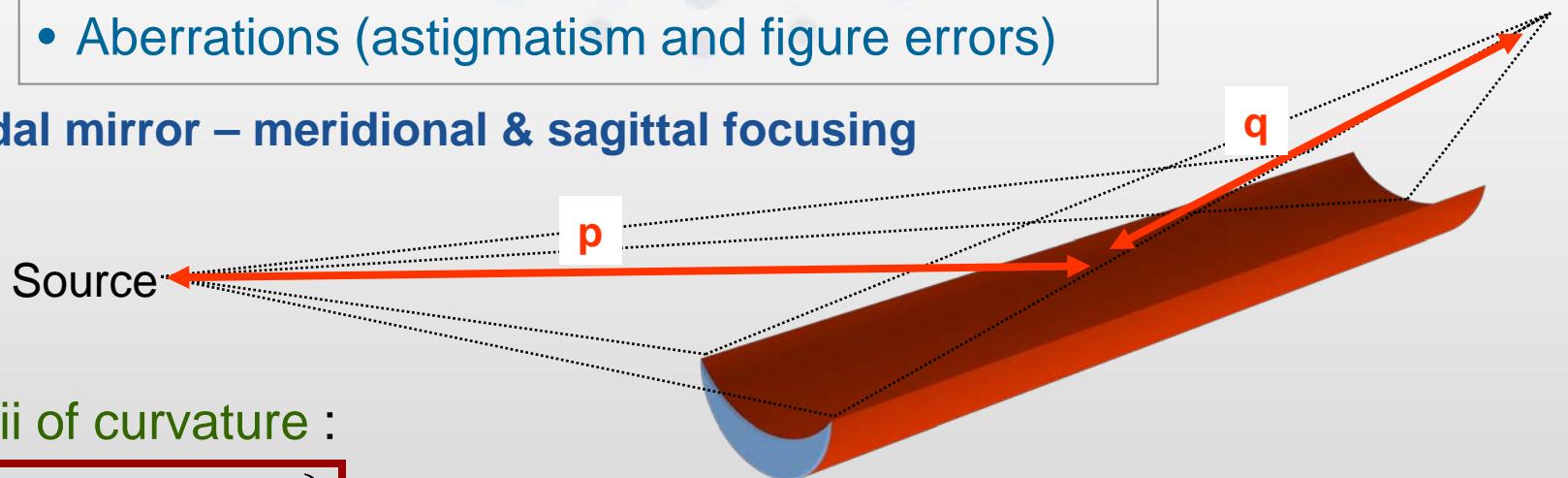
Most SR Mirrors are manufactured from Si, SiC or Glidcop



- Often long mirrors (> 1m)
- Off-axis geometry
- Point-to-point focusing => ellipsoidal figure
- Fabrication aspects -> not generally ellipsoidal
- Aberrations (astigmatism and figure errors)

Focus

e.g. toroidal mirror – meridional & sagittal focusing



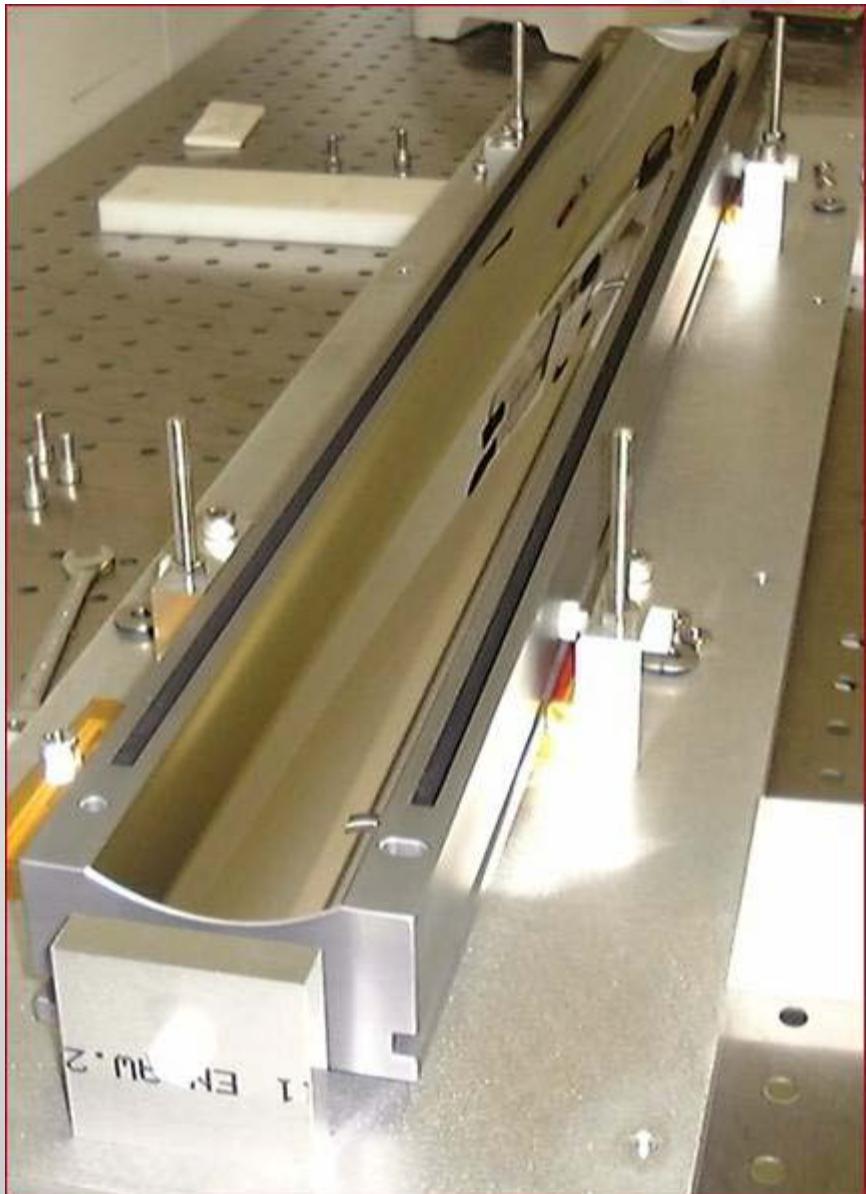
Radii of curvature :

$$\left. \begin{aligned} R_m &= \frac{2}{\sin \theta_i} \left(\frac{pq}{p+q} \right) \\ R_s &= 2 \sin \theta_i \left(\frac{pq}{p+q} \right) \end{aligned} \right\}$$

$$R_s \approx R_m \theta^2$$

$$\theta = 10 \text{ mrad}$$

$$\begin{aligned} R_s &\sim \text{mm} \\ R_m &\sim \text{km} \end{aligned}$$



Material-coating: Silicon-Pt

Supplier: SESO (France)

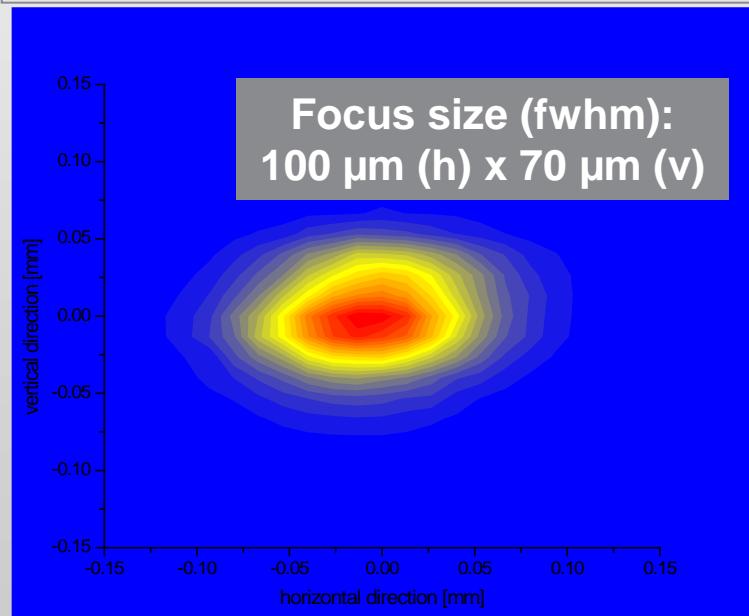
Roughness $\leq 2\text{\AA}$ rms

Radii of curvature:

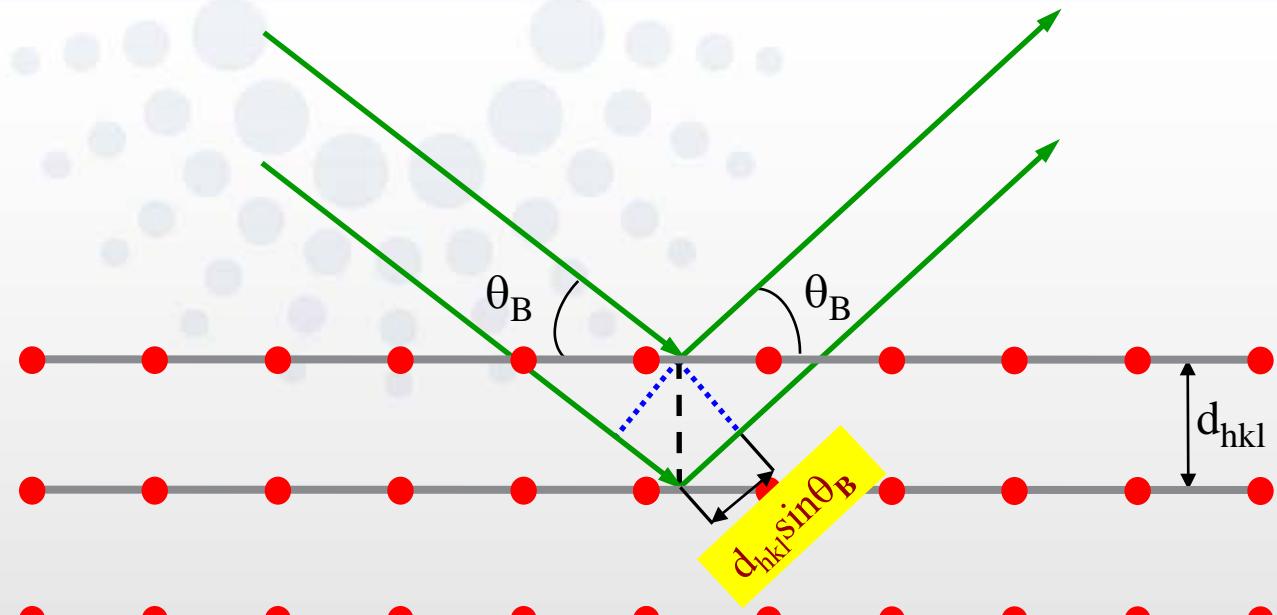
- Sagittal: 71.60 mm
- Meridional: 25 km

Slope error (RMS)

- 0.7 μrad over 450 mm
- 1.0 μrad over 900 mm



X-ray diffraction results from elastic scattering of X-rays from structures with long-range order. For X-ray optics generally concerned with **highly perfect single crystals** cf neutron mosaic crystals



$$\text{Bragg equation: } 2d_{hkl} \sin \theta_B = n\lambda$$

- Incident X-rays are “reflected” at atomic planes in the crystal lattice
- Path difference** of the rays $2d_{hkl} \sin \theta_B$
- Constructive interference if the path difference amounts to λ ($n \lambda$?)

$h k l$ are usually used, (e.g. 1 1 1, 3 3 3, 4 4 4), these are not Miller indices, but Laue indices, or “general Miller indices”.

A crystal monochromator slices out a narrow energy band from incident beam. Energy, E, determined by incidence angle, θ_B , of X-ray beam onto crystal planes according to Bragg equation:

$$E = \frac{hc}{\lambda} = \frac{hc}{2d_{hkl} \sin \theta_B}$$

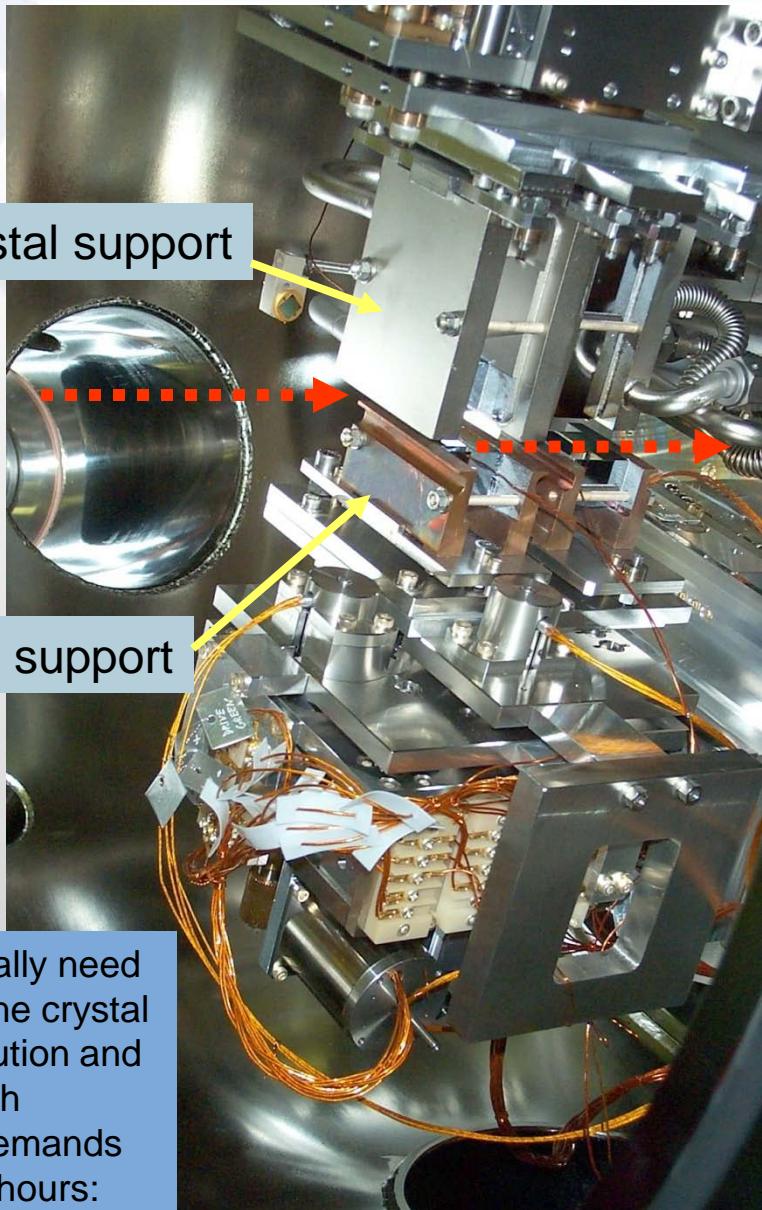
c = light velocity
 h = Planck's constant

Energy width of beam depends upon type of crystal and reflecting planes used (described by angular Darwin width ω_s) & divergence of incident beam, ψ_0

$$\frac{\Delta E}{E} = \frac{\Delta \lambda}{\lambda} = \sqrt{\omega_s^2 + \psi_0^2} \cot \theta_B$$

e.g. **Si 111 reflexion**,
 $d_{hkl} = 3.1355 \text{ \AA}$
 $\omega_s = 10.7 \mu\text{rad}$ (@ 8keV):
 $\theta_B = 14^\circ$
with a parallel incident beam:
 $\Delta E/E = 1.4 \cdot 10^{-4}, \Delta E = 1.1 \text{ eV}$

Monochromators typically need to be able to position the crystal planes with μrad resolution and similar repeatability with particularly stringent demands on stability over many hours:



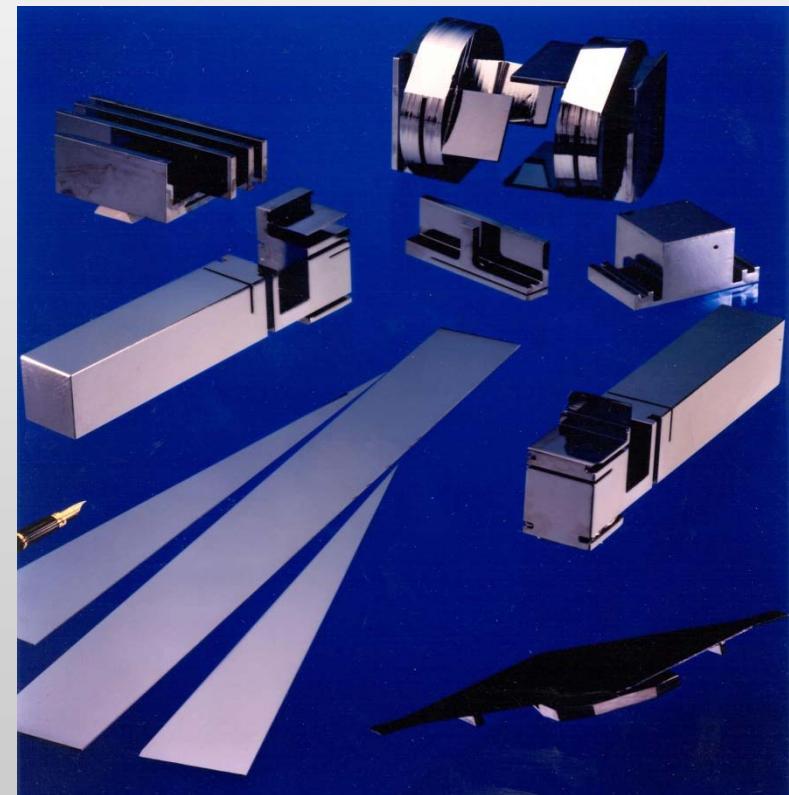
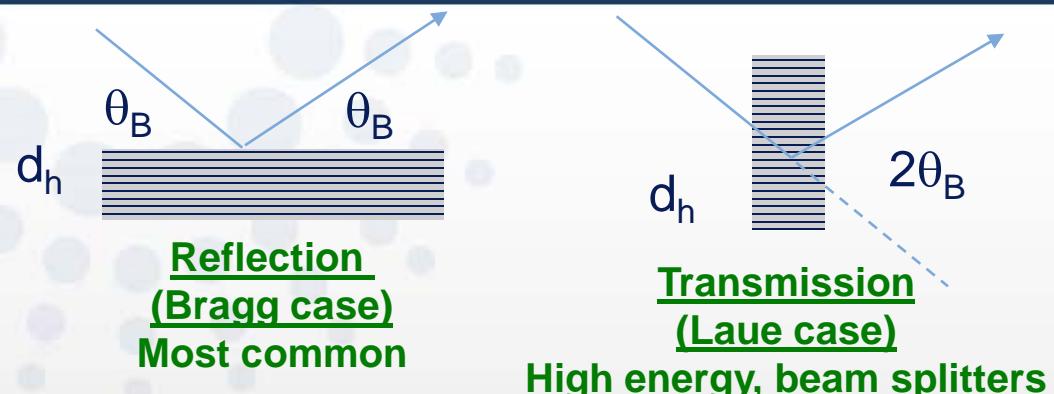
2 principal geometries:

Applications

- High resolution monochromator / analyser
 - $10^{-8} < \Delta E/E < 10^{-3}$
- Focussing monochromators
 - bent crystals
- Collimation / beam expander
 - asymmetrical cut
- Phase retarder (polariser)

Technical requirements

- Perfect crystals exist (Si, Ge, Diamond?...) but they must be tailored into monochromators
 - orientation, cutting, etching and polishing
 - strain free crystal preparation, accurate and stable mounting
- Appropriate cooling scheme



high reflectivity x-ray mirrors...
or synthetic crystals



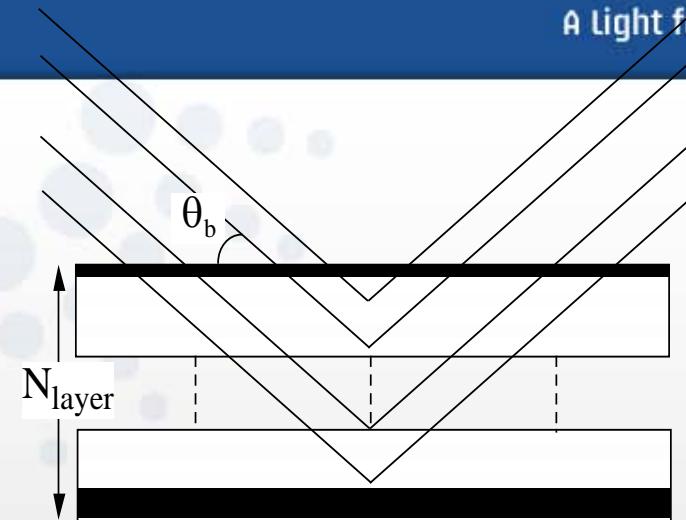
single boundary

For $\theta_i > \theta_c$

$E_r = r E_0$ where E_r, E_0 are reflected and incident wave amplitudes, r is the amplitude reflectivity

$r < 10^{-2}$ and $R = |r|^2 < 10^{-4}$

$$R \propto \frac{1}{\sin^4 \theta_i}$$



multiple boundaries

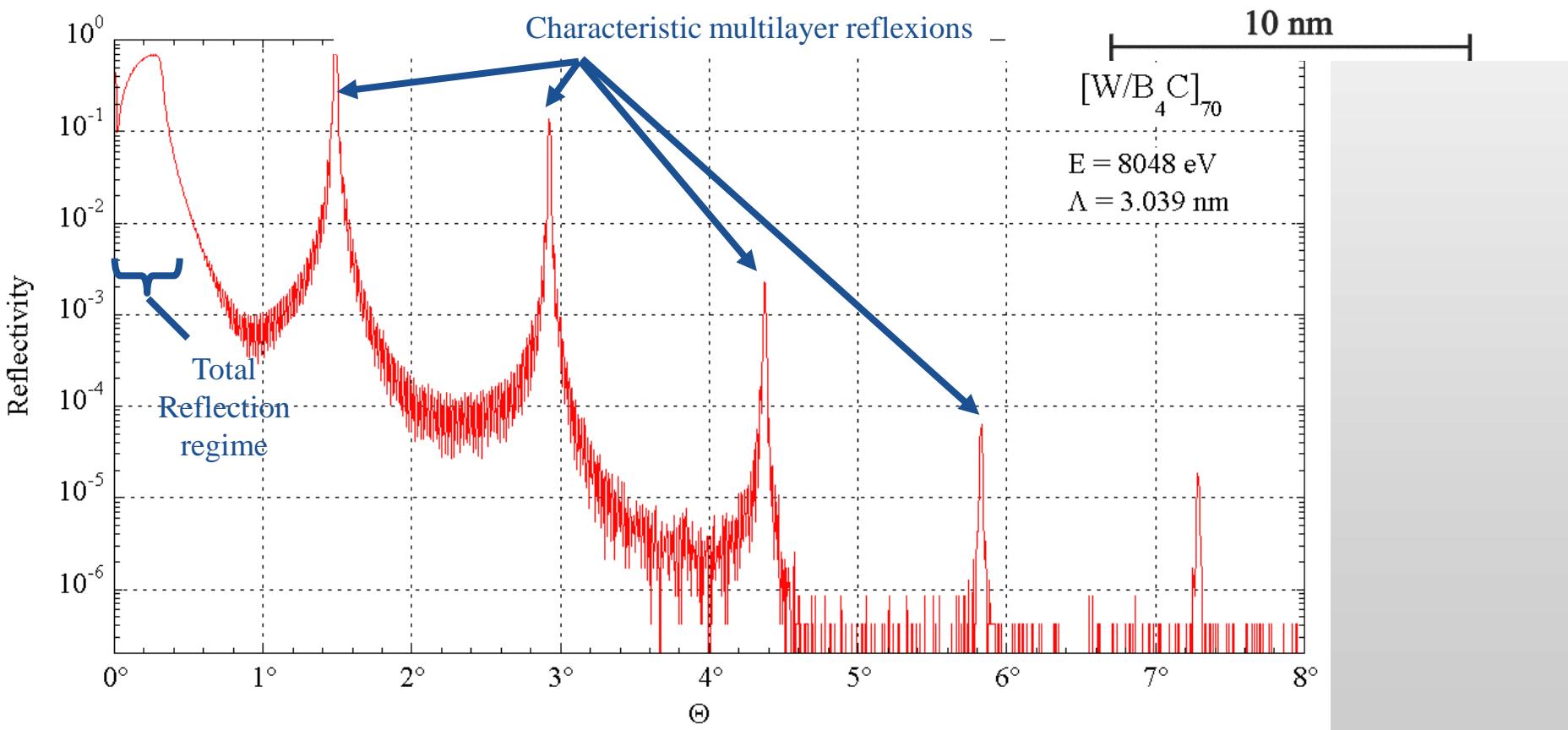
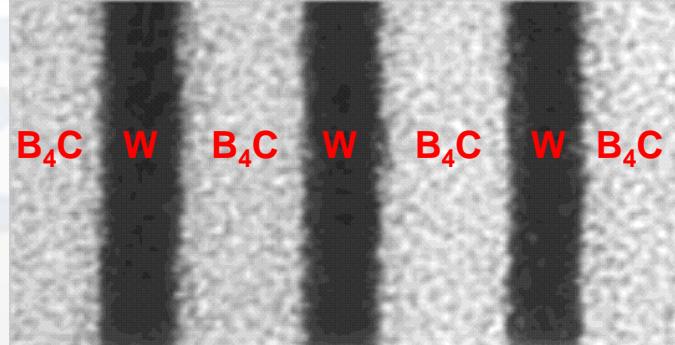
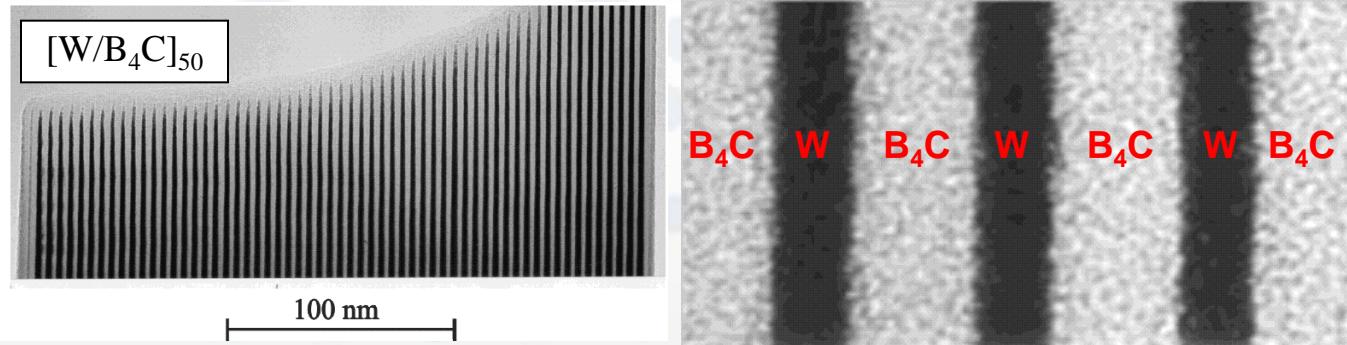
ideally $|r| \times N_{layer} \rightarrow R \rightarrow 1$

$n_1 = 1 - \delta_1 + i\beta_1$ and $n_2 = 1 - \delta_2 + i\beta_2$

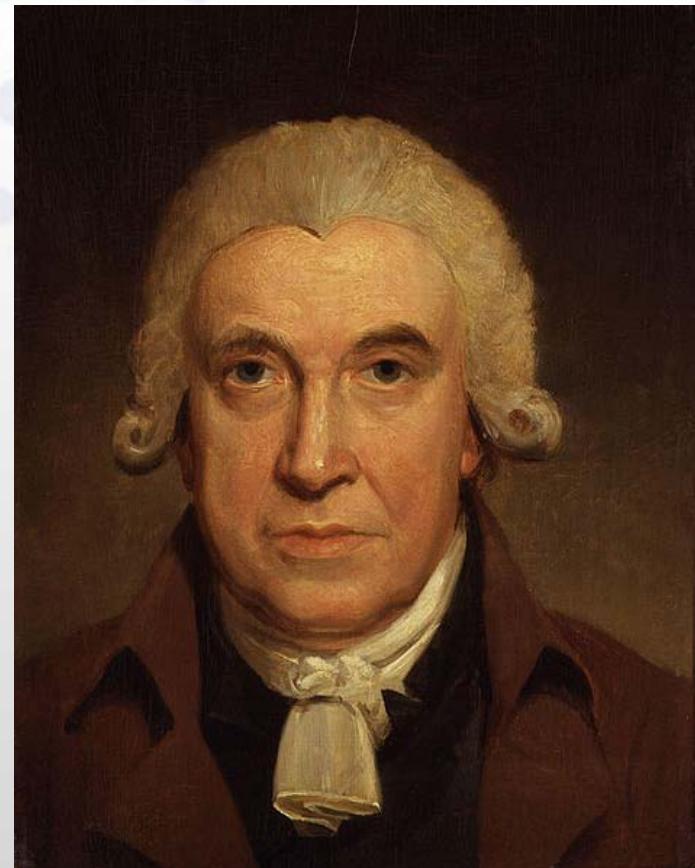
$$R \propto \frac{\Delta\delta^2 + \Delta\beta^2}{4} \frac{N_{layer}^2}{\sin^4 \theta_b}$$

- Wide energy band-pass monochromators, some soft X-ray monochromators
- Focusing : θ_b multilayer $>>$ θ_c mirror \rightarrow multilayer length $<<$ mirror length
lower spherical aberrations ($\sim L^2$), increased numerical aperture

Typical X-ray reflectivity scan of a multilayer

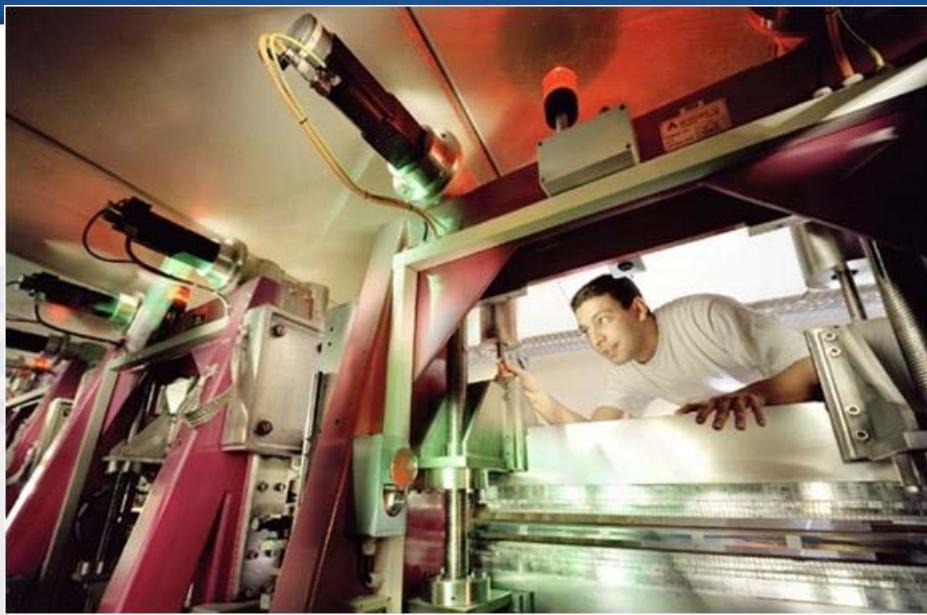
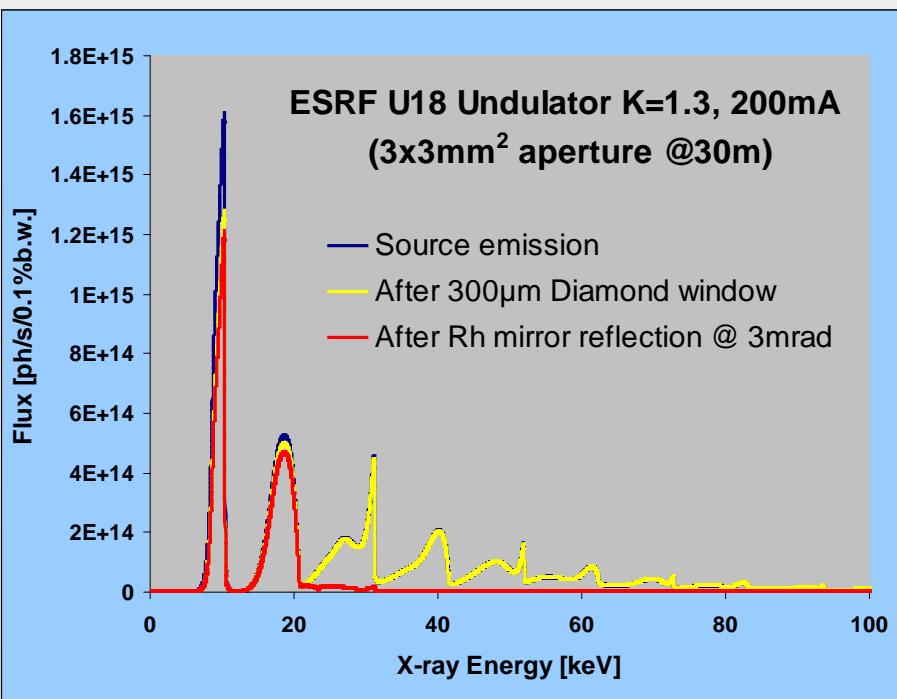


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James Watt
1736-1819

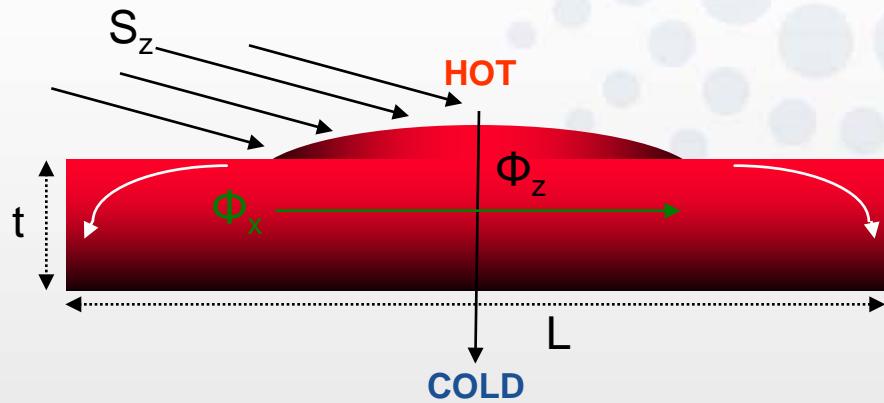
- ESRF U18 Undulator L=1.65m K=1.3, 90 periods, 200mA Storage Ring Current
- Total Emitted Power = **4.5kW**
- Through 3x3mm aperture @ 30m = **1.4kW**
- On-axis Power density **210W/mm²**



- 300μm polished diamond absorber (high pass Energy filter) **absorbs 135W**
- Rh-coated mirror reflecting at 3mrad (low-pass energy filter) **absorbs 700W**
- Around 550W incident on monochromator crystal – **essentially all absorbed**

- efficient cooling to prevent from melting
- minimization of induced thermal deformation
- materials resistant to intense X-ray beams

Gaussian intensity profile



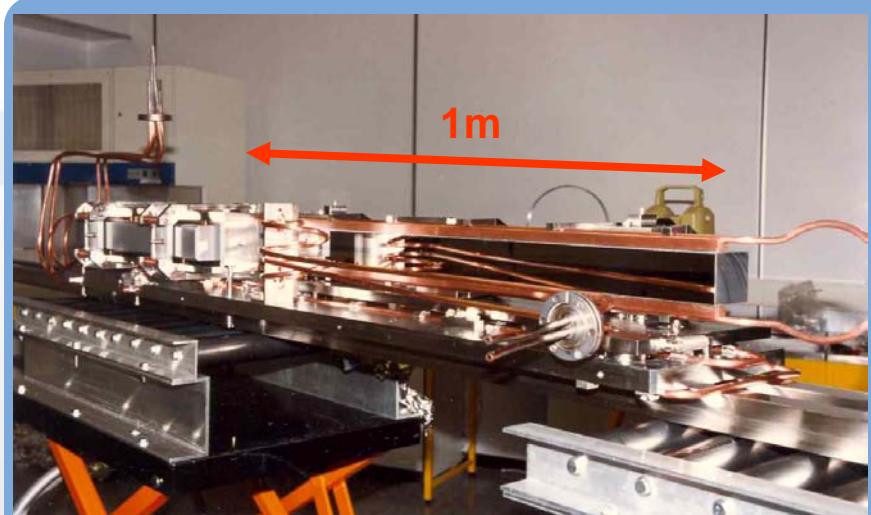
- Φ_x : local variation of thickness (thermal "bump")

$$\Delta_{bump} = \frac{\delta z}{\delta x} \propto \frac{\alpha}{\kappa} G P_s$$

- Φ_z : differential expansion hot-cold sides (thermal "bending")

$$\Delta_{bending} = \frac{\delta x}{\delta z} \propto \frac{\alpha}{\kappa} G P_t$$

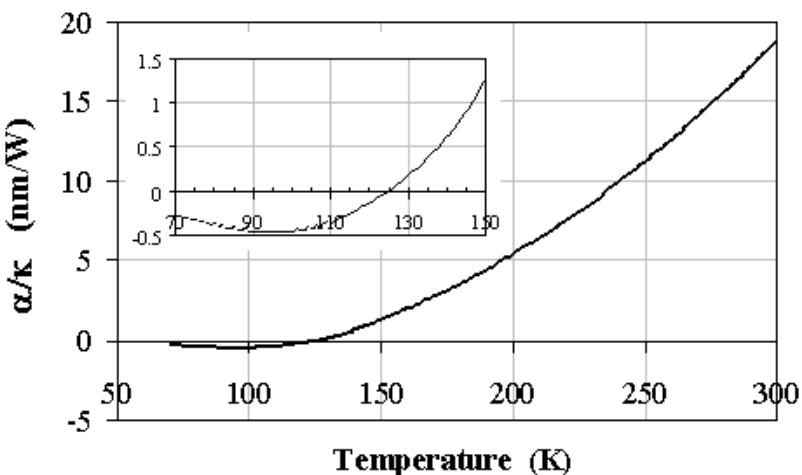
Generally mirror is over-illuminated to minimise Φ_x



Double Si mirrors (mounted face-to-face) with side-cooling geometry (water)

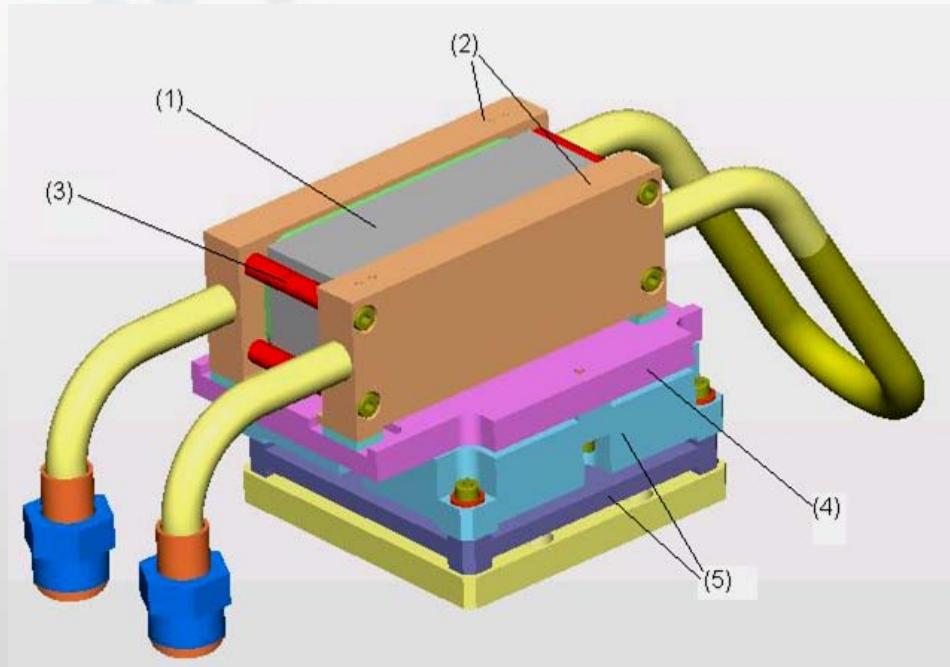
$$\left. \begin{array}{l} \alpha : \text{thermal expansion} \\ \kappa : \text{thermal conductivity} \\ G : \text{cooling geometry factor } (\sim 0.01 - 1) \\ P_s : \text{Power density} \\ P_t : \text{Total power} \end{array} \right\}$$

- Darwin widths of typical crystal reflexions are in the μrad range and below:
 - Monochromator performance is particularly sensitive to thermal deformations of diffracting crystals
 - By cooling Si to cryogenic temperatures (LN₂ sufficient) – thermal deformations due to beam absorption can be minimised.



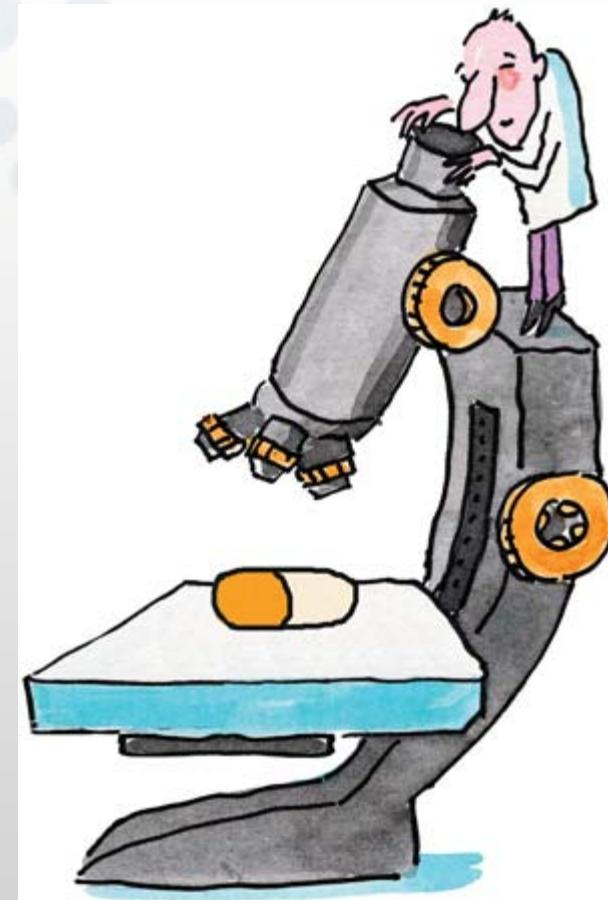
Ratio of thermal expansion and thermal conductivity of Si α/k vs temperature

Example of ESRF first crystal assembly:
(1) silicon crystal; (2) copper cooling blocks with internal fins; (3) invar clamping rods; (4) invar base plate; (5) ceramic insulating plates



- Crystal is side cooled with cooling blocks clamped with pressures between 5-10bar
- Deformation of crystal planes due to clamping <1 μrad
- Over 17 ESRF beamlines using LN₂ cooled monochromators

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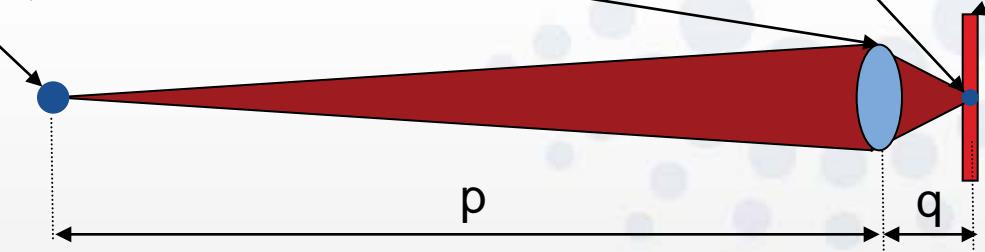
Probe forming

Source, o

objective lens, focal length f

Probe, i

sample



Thin lens

$$\frac{1}{p} + \frac{1}{q} = \frac{1}{f}$$

Magnification,

$$M = \frac{i}{o} = \frac{q}{p}$$

For fixed p , $M \uparrow \Rightarrow f \downarrow$

- Detection of signals arising from interaction of small probe with sample
- Sample scanned through beam to build ‘image’ pixel by pixel

Full field imaging

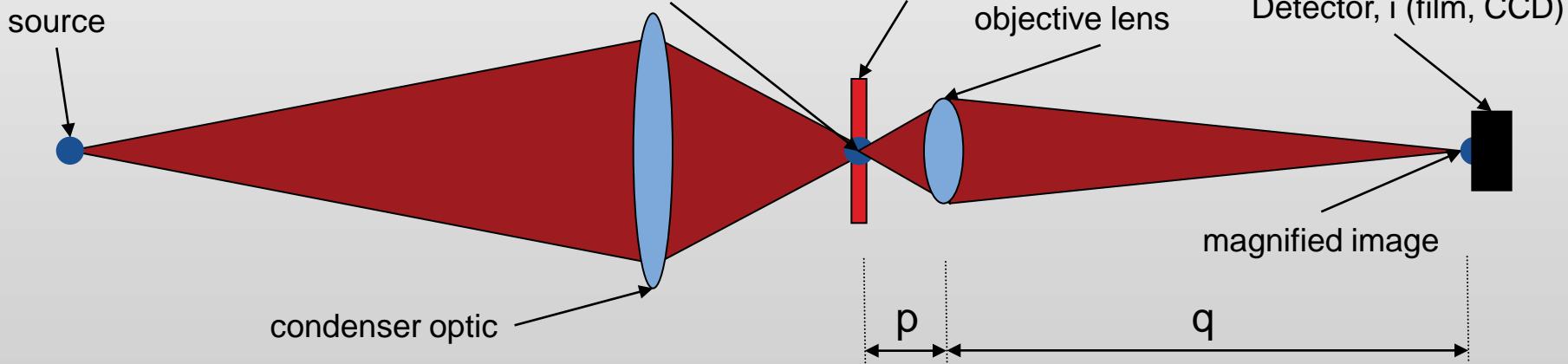
source

illuminated zone

Sample, o

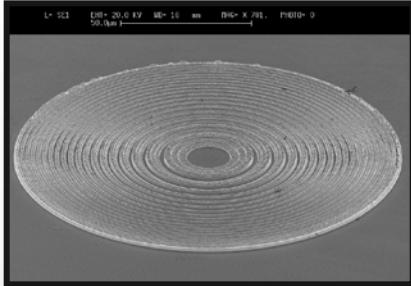
objective lens

spatially resolving
Detector, i (film, CCD)



- Condenser optic → illuminated zone on sample
- Objective lens → magnified image of sample on spatially resolving detector

Diffractive optics

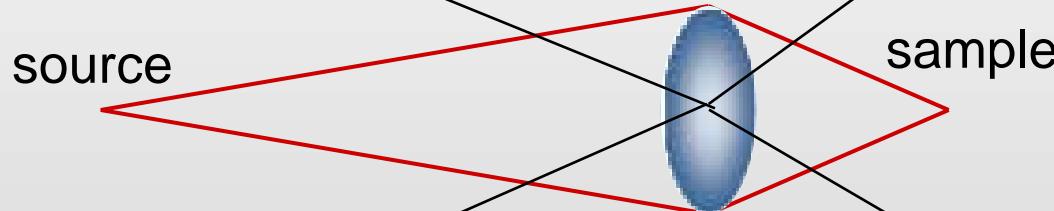


- **Fresnel zone-plate (FZP)**
- **Bragg-Fresnel**
- **Crystals**
- **Multilayers**

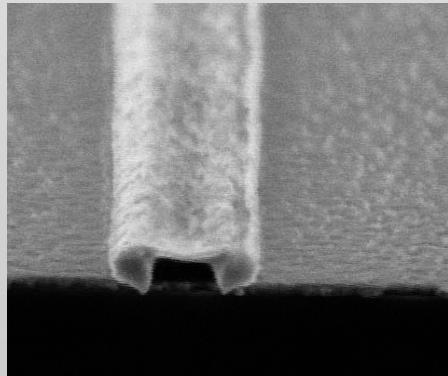
X-ray reflectors



- **Kirkpatrick-Baez**
- **Wolter mirror**
- **Ellipsoidal mirror**
- **Micro-channel**
- **(Poly)capillaries**

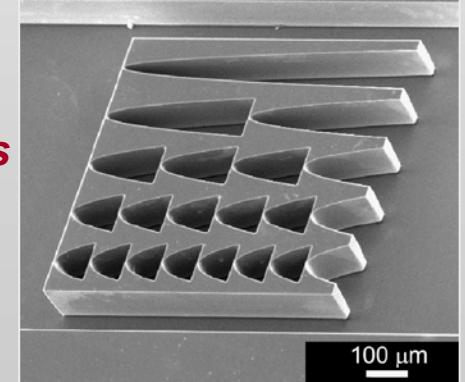


X-ray resonators



- **Waveguides**

Refractive lenses



- **Compound refractive lenses (CRL)**

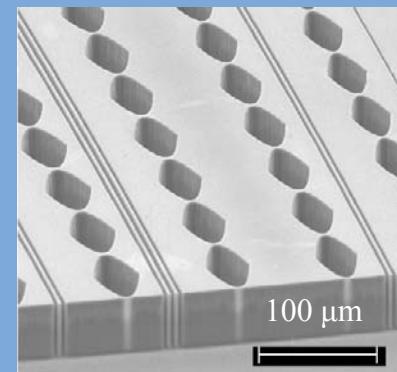
- There are no insurmountable theoretical barriers to achieving sub-10nm resolution X-ray focusing
- BUT the technological challenges are considerable



Reflective Optics:
Figure Error
Thermal, mechanical stability,
Graded multilayers



Diffractive Optics:
Feature size/placement
Structure heights
(efficiency)

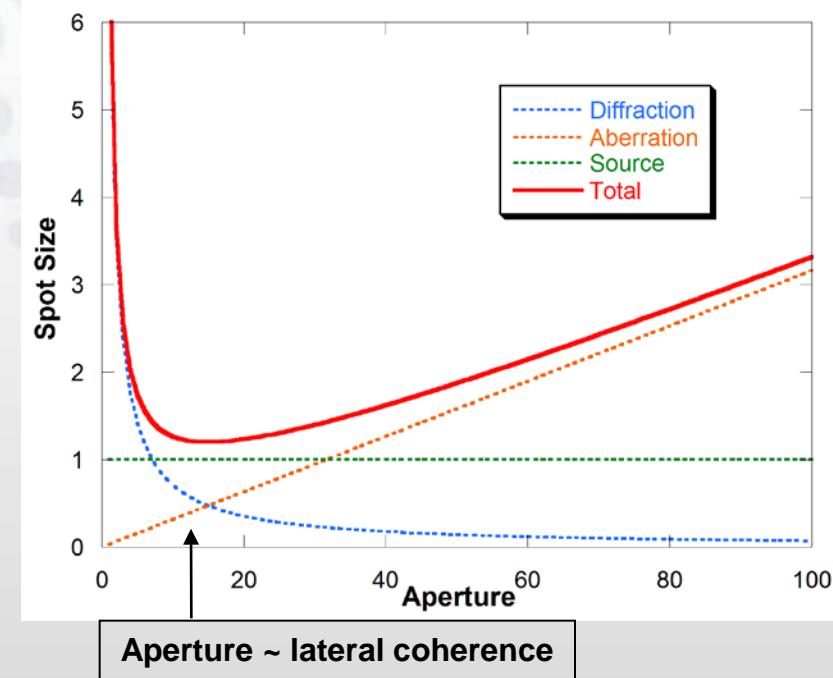
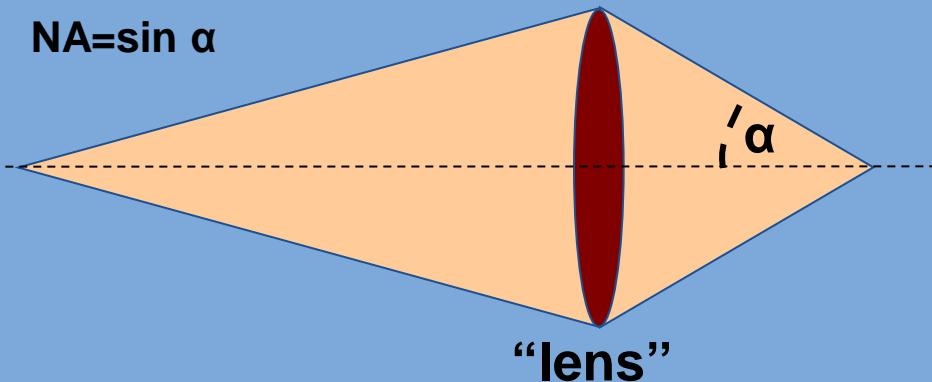


Refractive Optics:
Absorption limited numerical aperture
Side-wall roughness

Resolution is not the only parameter. Often photon flux, focus stability is at least as important. Large acceptance, high efficiencies...

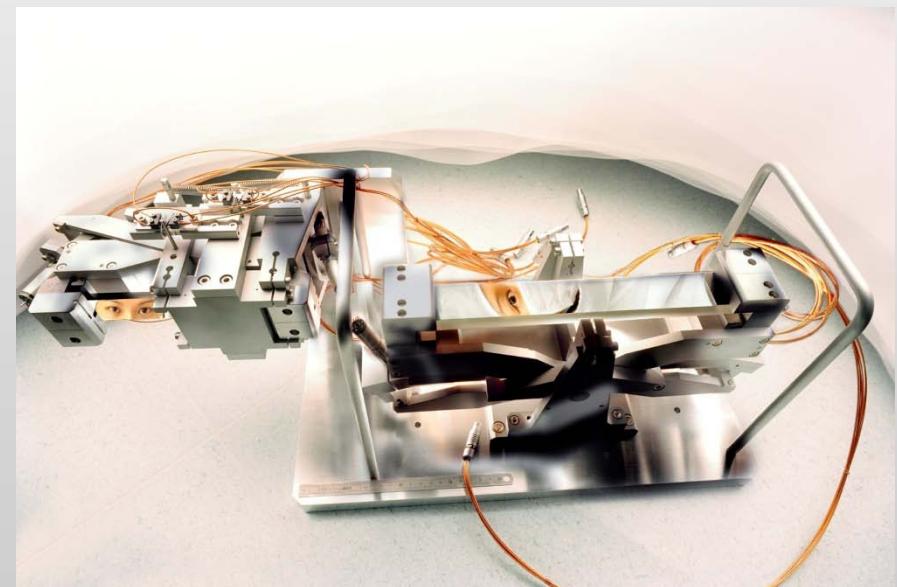
- High demagnifications **but** fundamental limit: Rayleigh criterion:

Diffraction limited resolution = $0.61\lambda/\text{NA}$
(for circular aperture)
 λ = wavelength
NA = Numerical Aperture



Increase NA – longer mirrors & higher grazing angles (MLs), larger diameter CRL, ZPs
Generally aberrations or flux loss will impose resolution limits
Best current technologies for hard X-rays NA ~ 0.003

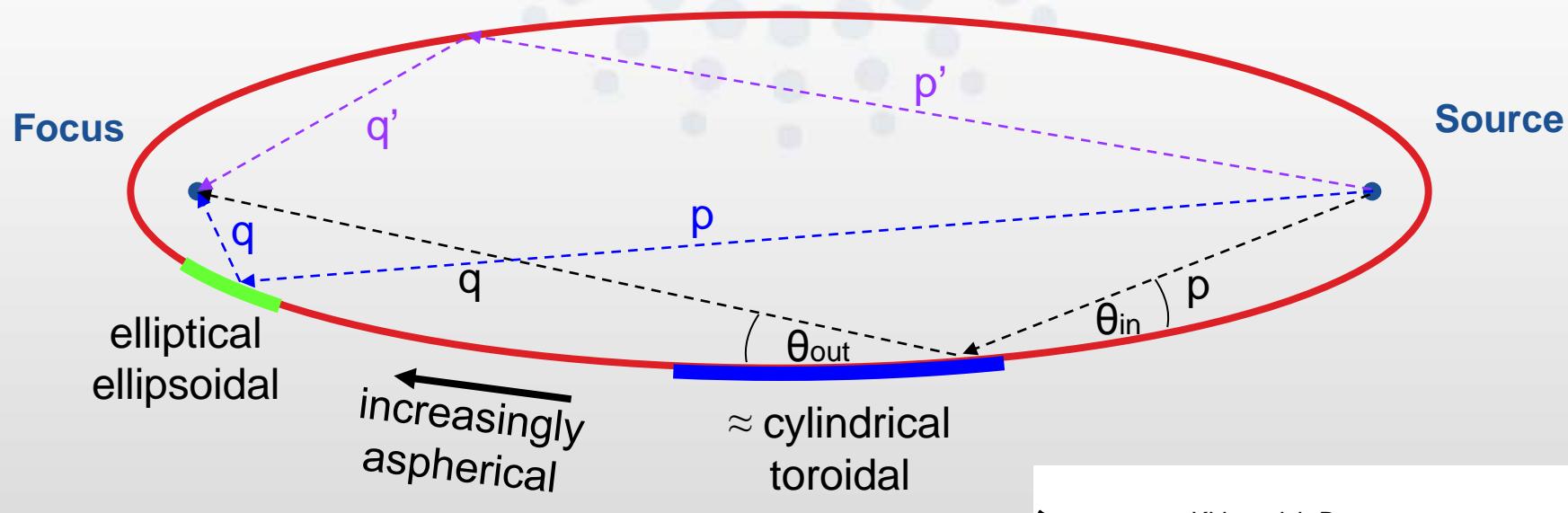
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Ellipse: $p + q = \text{constant}$, $\theta_{\text{in}} = \theta_{\text{out}}$

Focusing: equivalent optical path lengths from source-to-focus

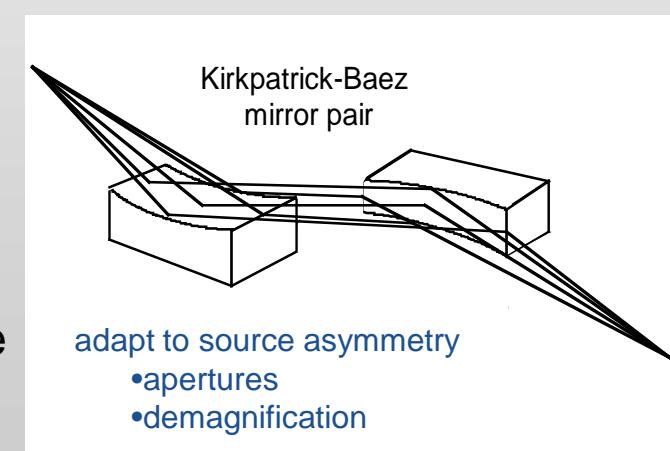
'Ideal' mirror would have an **elliptical (2D)** or **ellipsoidal (3D)** surface figure



$$\text{focus size} \approx \text{source size} \times q/p$$

Micro/nanofocusing applications:

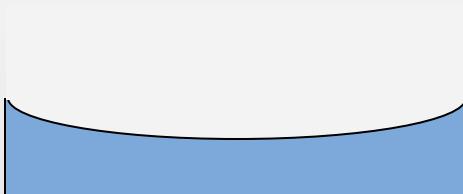
- good ellipsoidal mirrors not readily manufacturable
- perpendicular elliptical mirrors
 - Kirkpatrick-Baez (KB) configuration



Two basic approaches:

Static Figuring

- Elliptical figure polished into mirror substrate



Dynamic Figuring

- Elliptical figure by mechanical bending of a (usually flat) mirror substrate

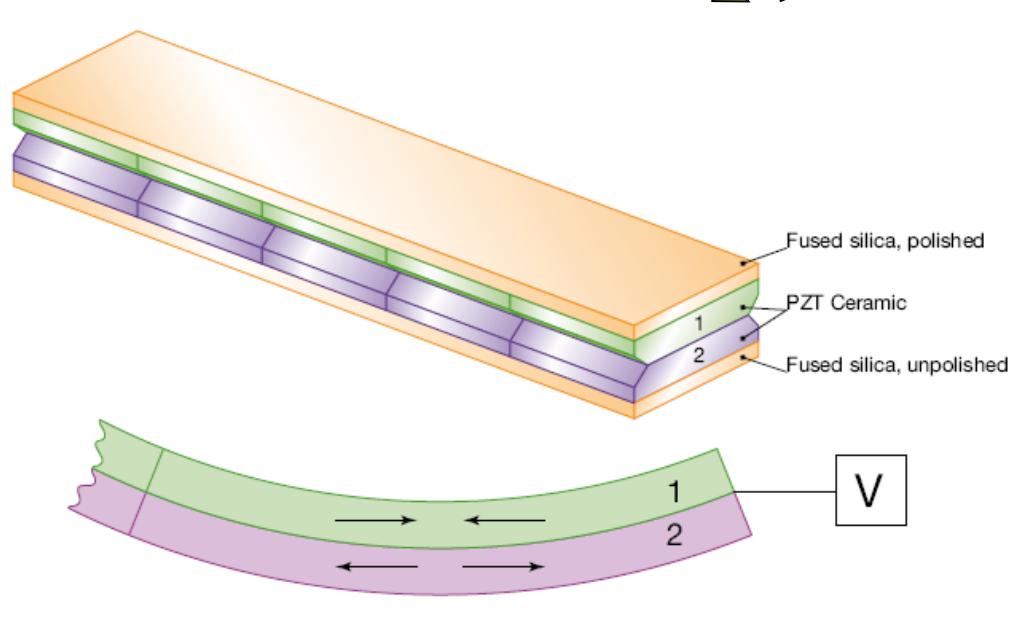


- Relatively simple mechanics
- OK for very short radius ellipses
- Lengthy/expensive fabrication
- Only optimised for one set of operating conditions (incidence angle, focusing distance)

- Simple substrate polishing
- Relatively cheap systems
- Active systems allowing modification of focusing parameters (permits use at variable energy with Multilayer coatings)
- Not well adapted for very short radius ellipse (mirror will break!)

- 2 major classes:
- Piezoelectric bimorph systems (ESRF, SESO, FMB-Oxford, ACCEL)
- Mechanically actuated systems (ESRF, ALS, APS, SOLEIL, Irelec, X-Radia)
- Extension of these technologies – increase number of actuators to correct local figure errors – active optics (several projects)

2 independent bending moments: Elliptical Figure

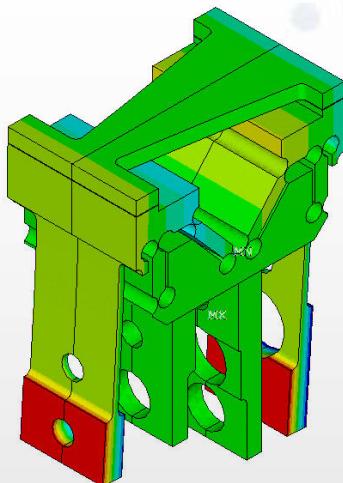


Principle of Bimorph Mirror (from FMB-Oxford)

2 independent actuators

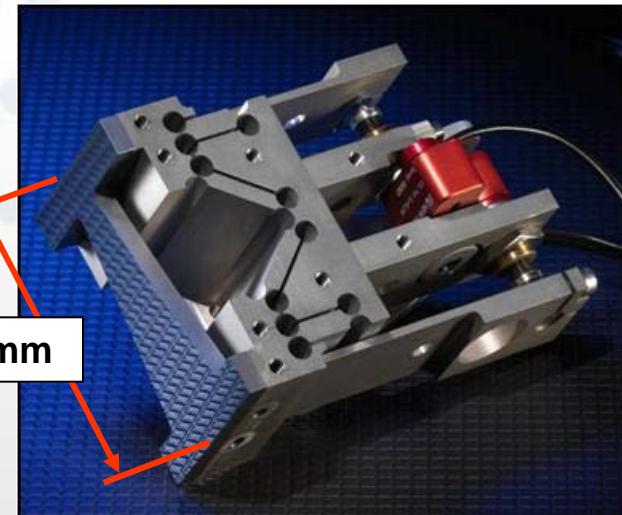
ESRF mirror bender based on monolithic flexure hinge technology

Full FEA
modelling
for shape
optimisation

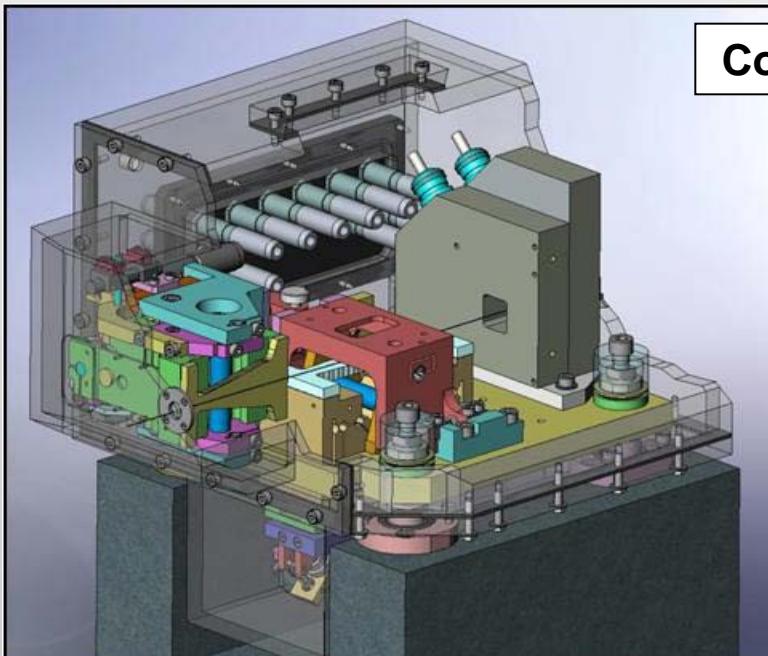


ID22-NI horizontally
focusing bender

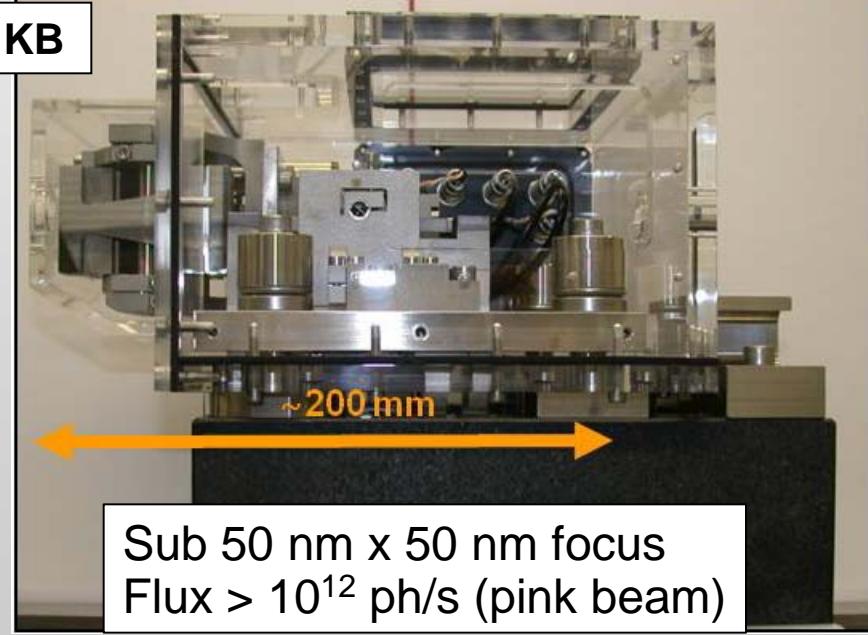
- Bonded optics
- Mirror width profile machined to $\pm 3\mu\text{m}$
- Close to fracture stress limit
- Optimized Si orientation



76mm



Complete KB



Thin gold test pattern

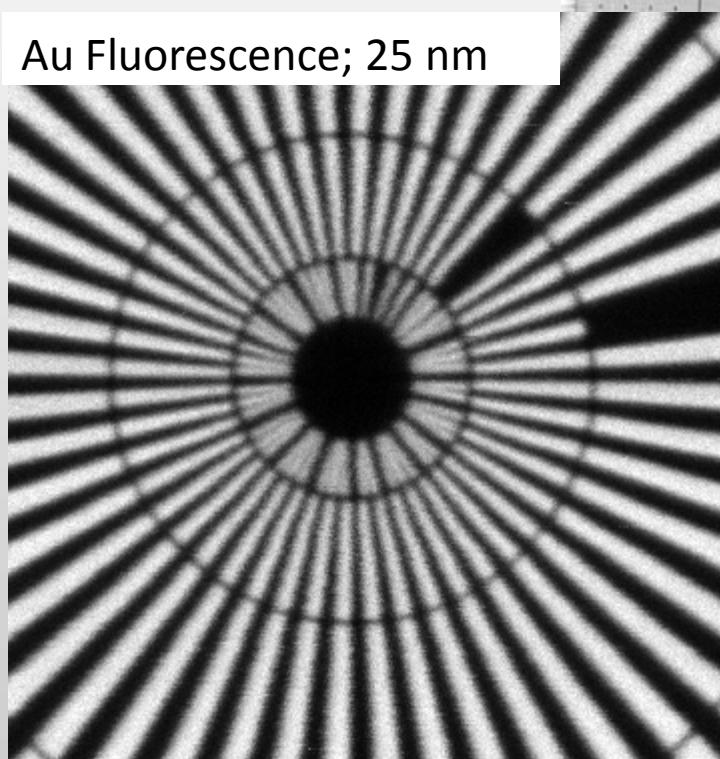
Innermost line width: 50 nm

Energy = 17.3 keV

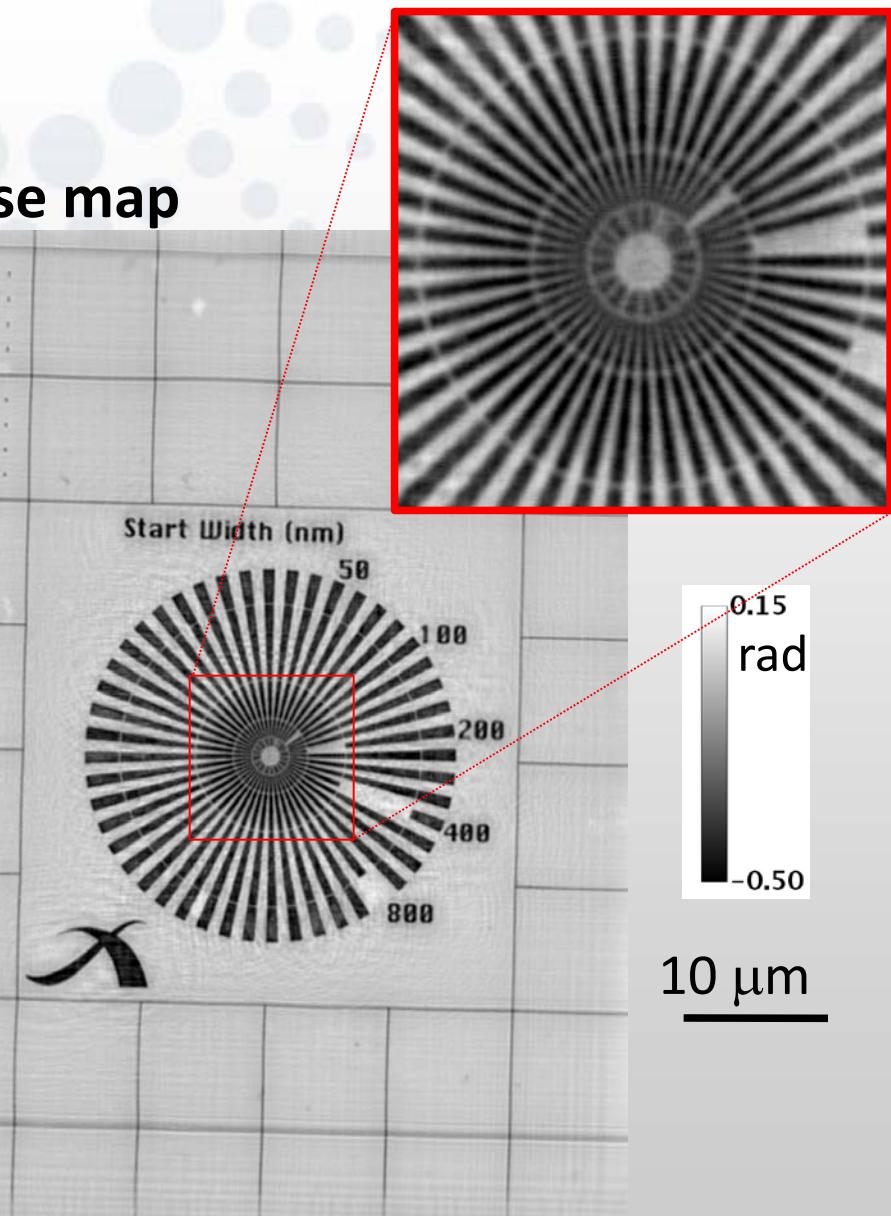
Field of view: 80 μm

Pixel size: 53 nm

Au Fluorescence; 25 nm



Phase map



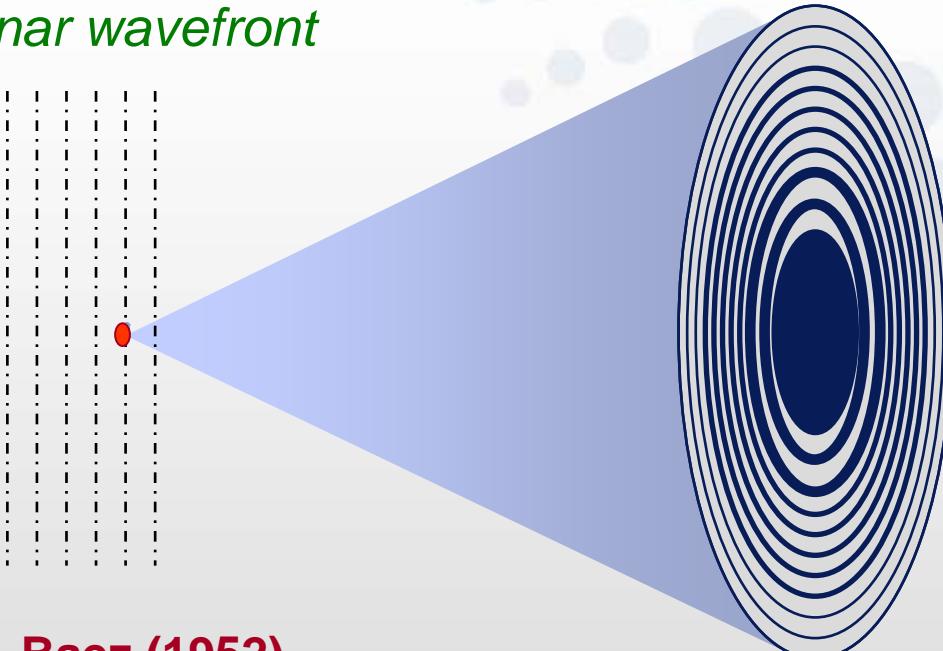
- **Introduction**
- General X-ray optics
- High heat-load optics
- X-ray micro-/nano-focusing
 - Reflectors
 - **Zone plates**
 - Refractive lenses
- Summary



Augustin-Jean Fresnel
1788-1827

Hologram (Fresnel Zones)

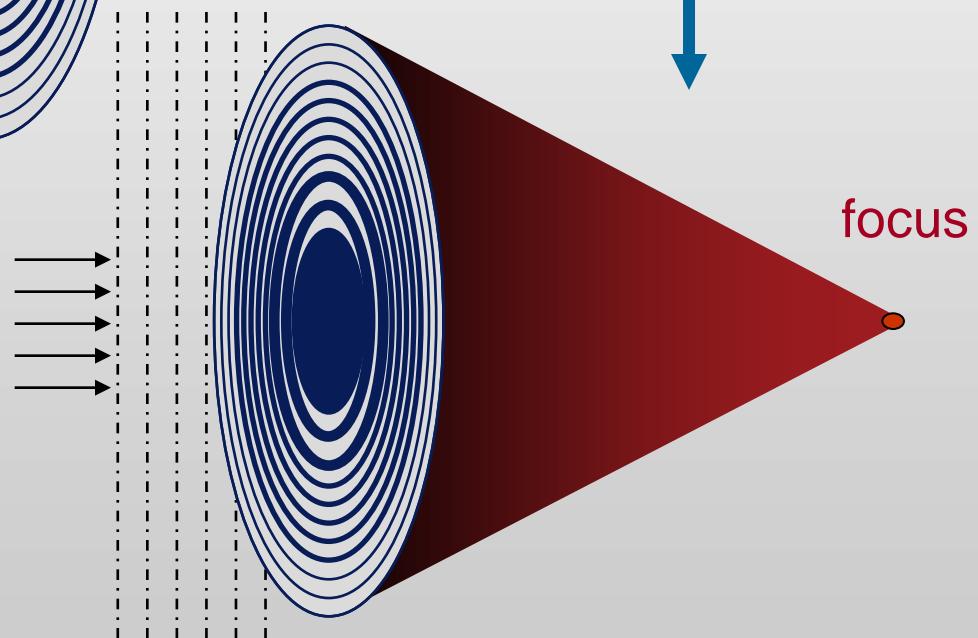
Planar wavefront



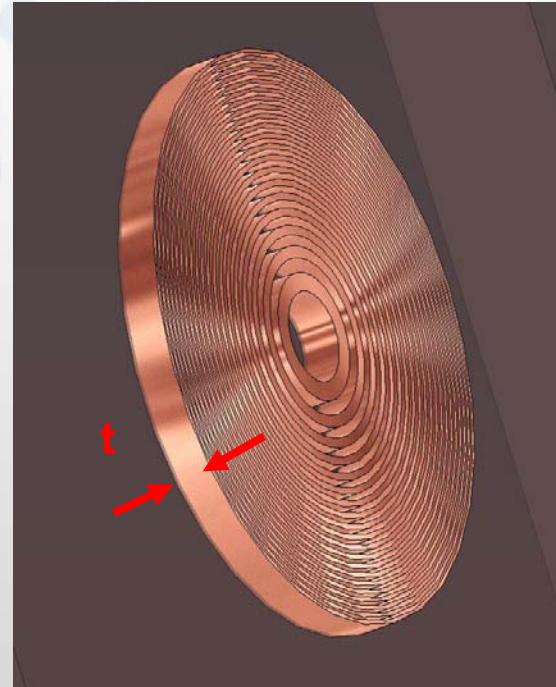
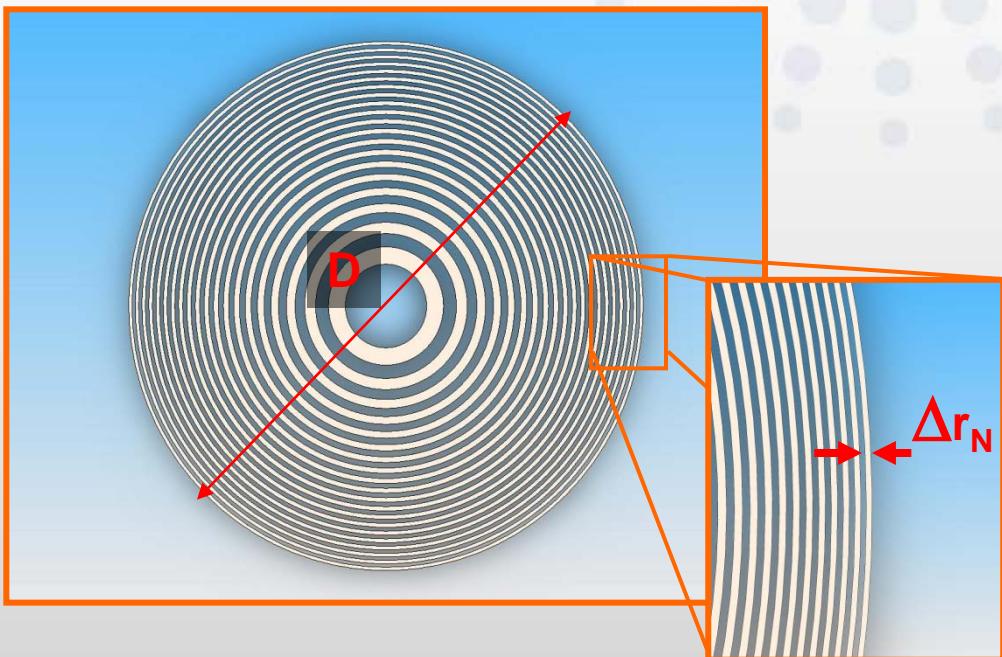
Baez (1952)
Schmahl (1969)
Kirz (1971)
Niemann (1974)

Gabor hologram of a point object

*Reconstruction
by
coherent illumination*

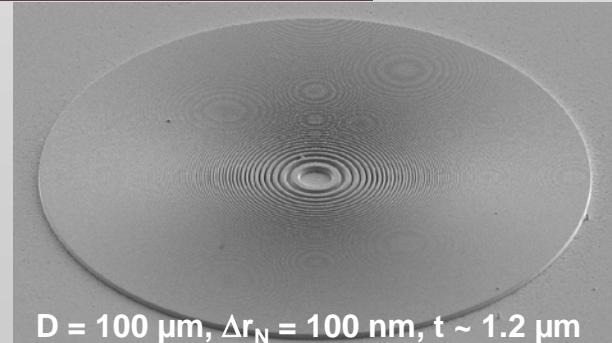


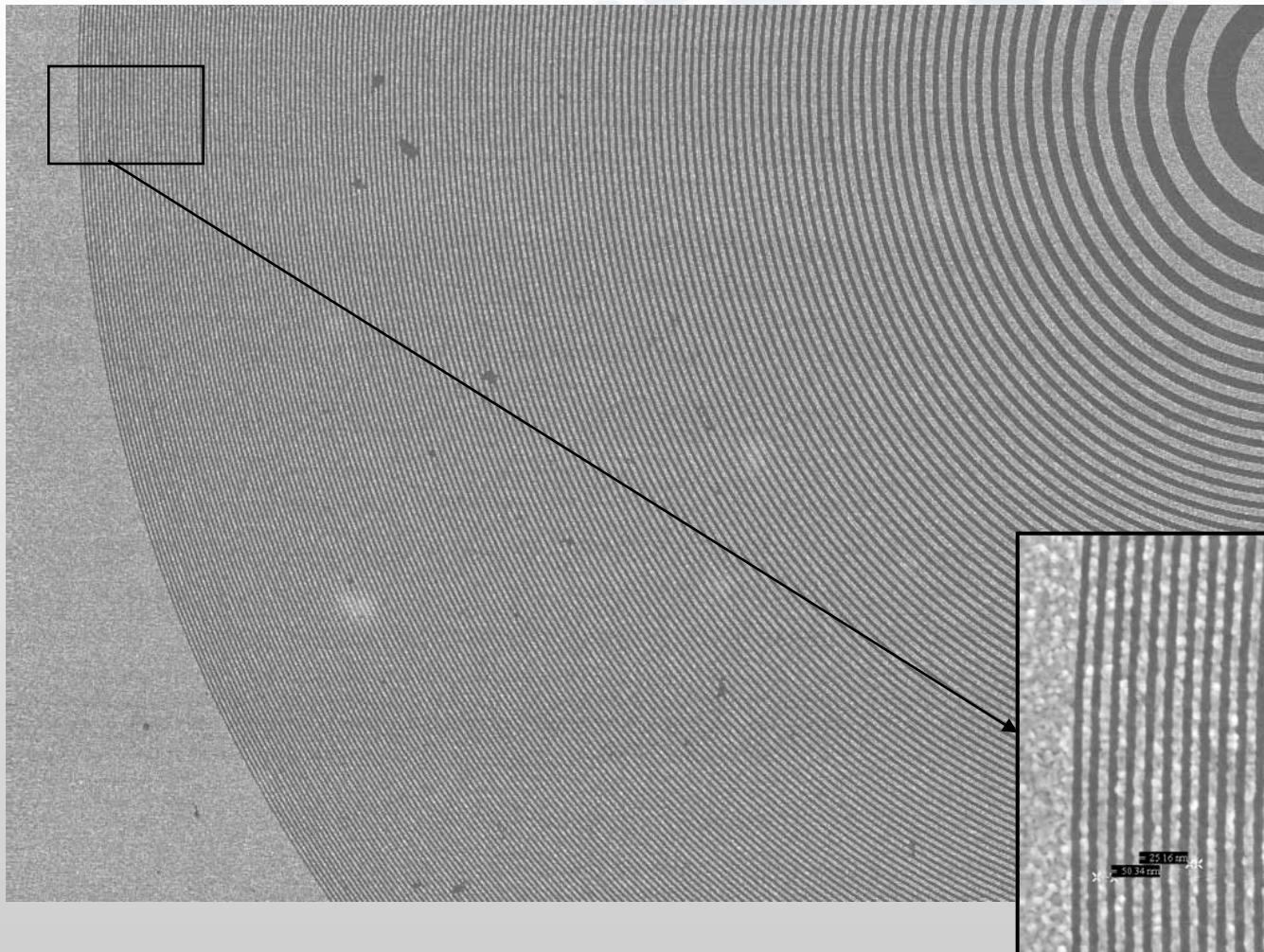
- Diffractive X-ray Lenses: Circular transmissive diffraction gratings with radially decreasing line width giving focusing effect



Alternate 'zones' modify phase/amplitude of incident wavefront: for material of thickness, t , wavelength, λ , refractive index $1-\delta-i\beta$, phase shift, $\Delta\phi$, is:

$$\Delta\phi = \frac{2\pi\delta t}{\lambda}$$

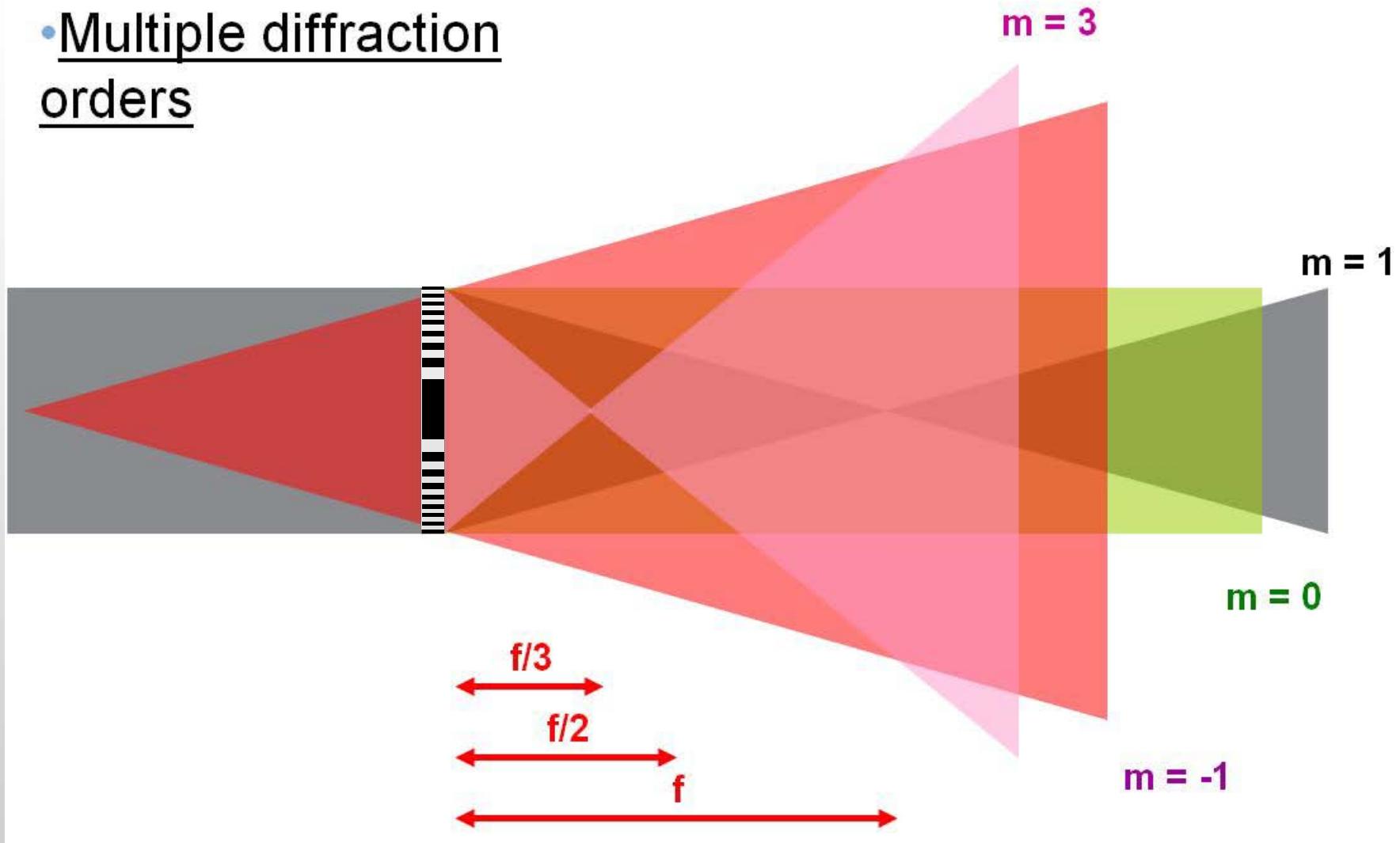


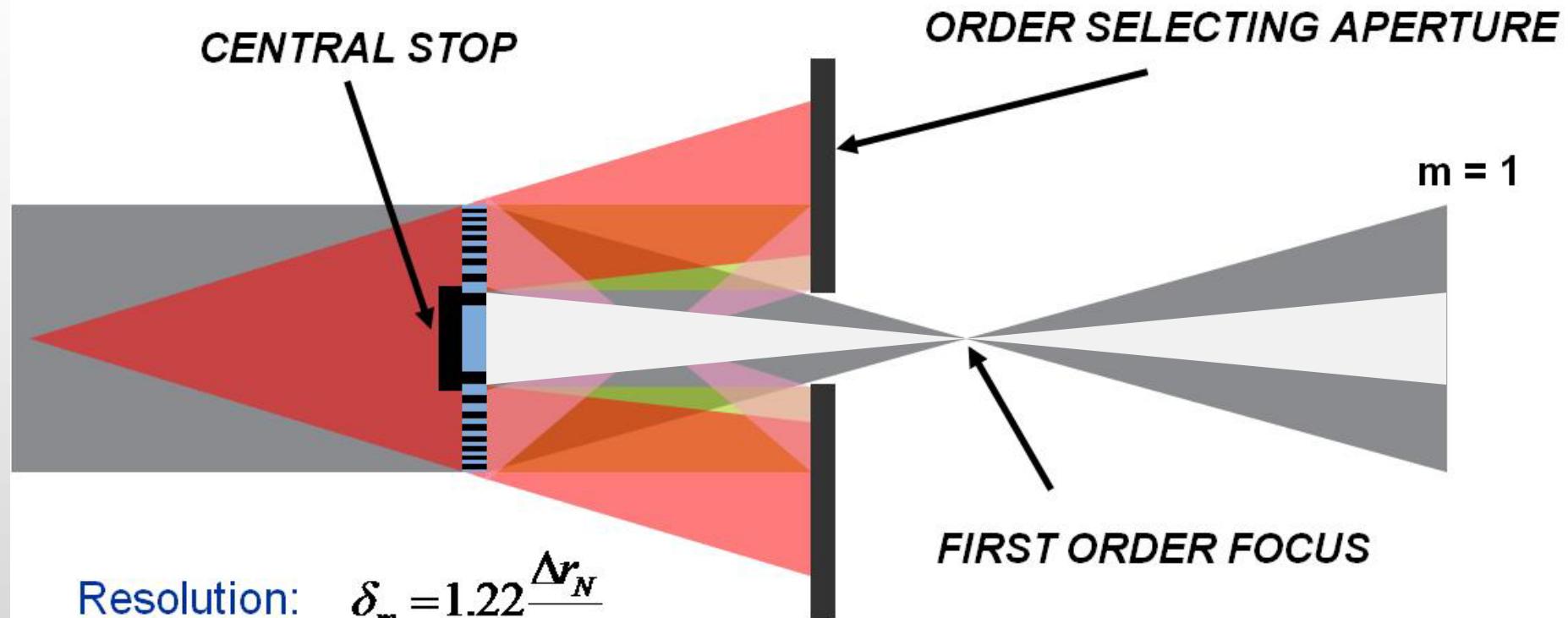


- $\Delta r_N = 25 \text{ nm}$
- $D = 63 \mu\text{m}$
- $N = 618$ zones
- $f = 650 \mu\text{m}$
- $\text{NA} = 0.05$
@ $\lambda = 2.4 \text{ nm}$

E. Anderson, Center for X-Ray Optics, LBNL, USA

- Multiple diffraction orders



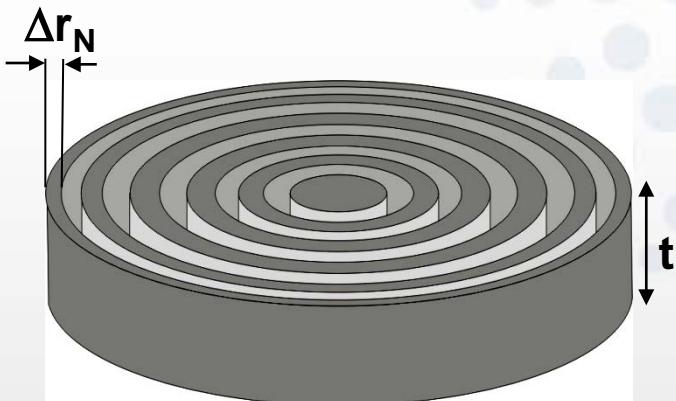
Rejection of the unwanted diffraction orders

Resolution: $\delta_m = 1.22 \frac{\Delta r_N}{m}$

Focal length: $f_m = \frac{D \Delta r_N}{m \lambda}$

Depth of focus: $DOF = \pm \frac{2 \Delta r_N^2}{m \lambda}$

structure height, t , critical for efficiency, Δr_N for resolution



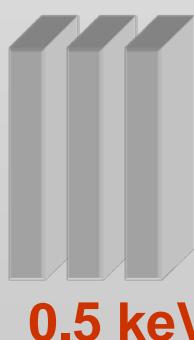
Material	t (μm)	ε (%)
$E=0.5\text{keV}$		
Ge	0.28	16
Ni	0.25	24
$E=2.0\text{keV}$		
Ni	0.60	25
Au	0.45	24
$E=8.0\text{keV}$		
Ta	1.70	32
W	1.50	33

Aspect ratio for $\Delta r_N=50\text{nm}$

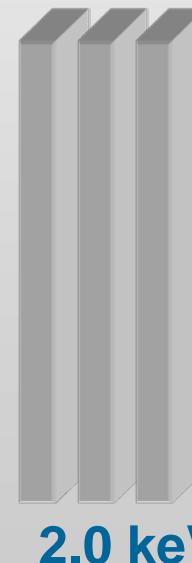
Practical limit for small Δr_N is $\sim 10\text{-}15:1$

Nickel
25%
12 : 1

Nickel
24%
6 : 1



0.5 keV



2.0 keV

Tantalum
32%
28 : 1

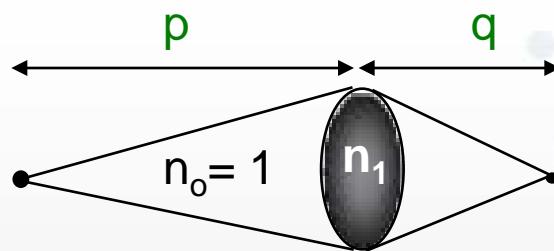


8.0 keV

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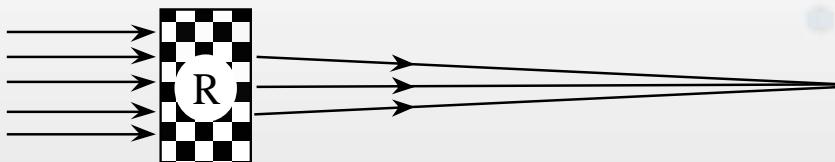


Willebrord Snellius
1580-1626



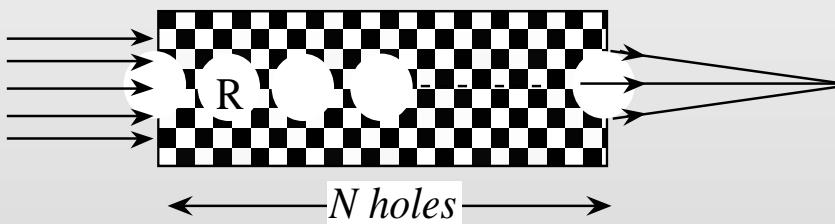
Gaussian lens equation: $\frac{1}{f} = \frac{2(n_1 - 1)}{R}$

Thin lens equation : $\frac{1}{f} = \frac{1}{p} + \frac{1}{q}$



$$\frac{1}{f} = \frac{2\delta}{R}$$

X-rays : $n = 1 - \delta + i\beta$



$$\frac{1}{f} = N \frac{2\delta}{R}$$

$n_1 < 1$: concave lens

Example :

Aluminium @ 10keV $\delta = 5.5 \cdot 10^{-6}$

1 hole of 100 μm radius : $f = 9 \text{ m}$

15 holes of 100 μm radius: $f = 60 \text{ cm}$

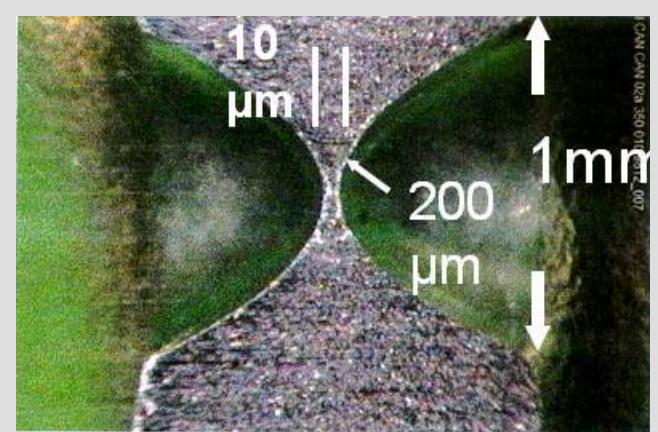
Advantages

- simplicity and low cost
- low sensitivity to heat load

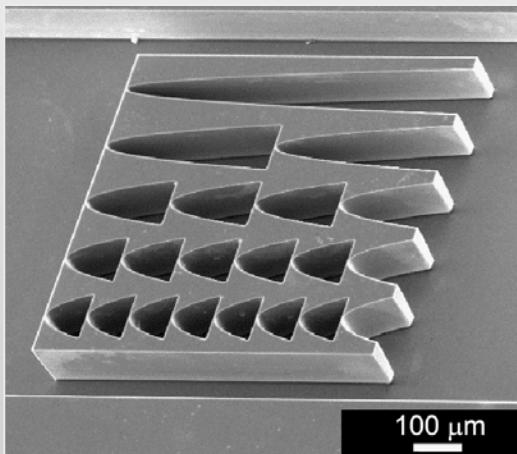
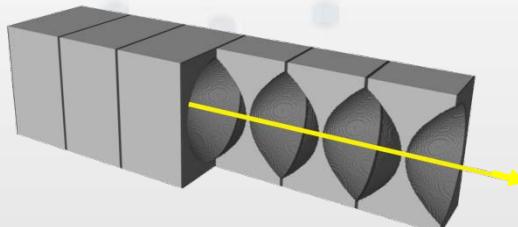
Disadvantages

- efficiency limited by absorption
- small aperture (limited resolution)
- strong chromatic aberrations

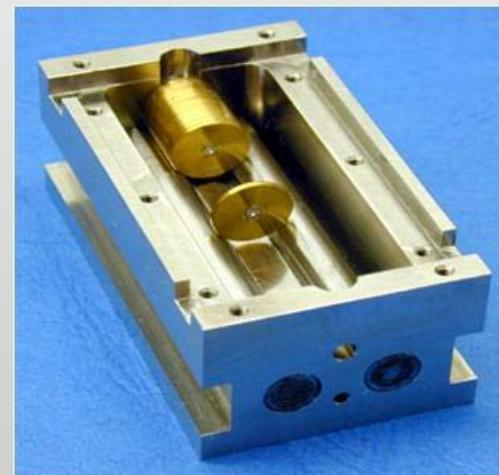
A. Snigirev et al. Nature, 384 (1996)



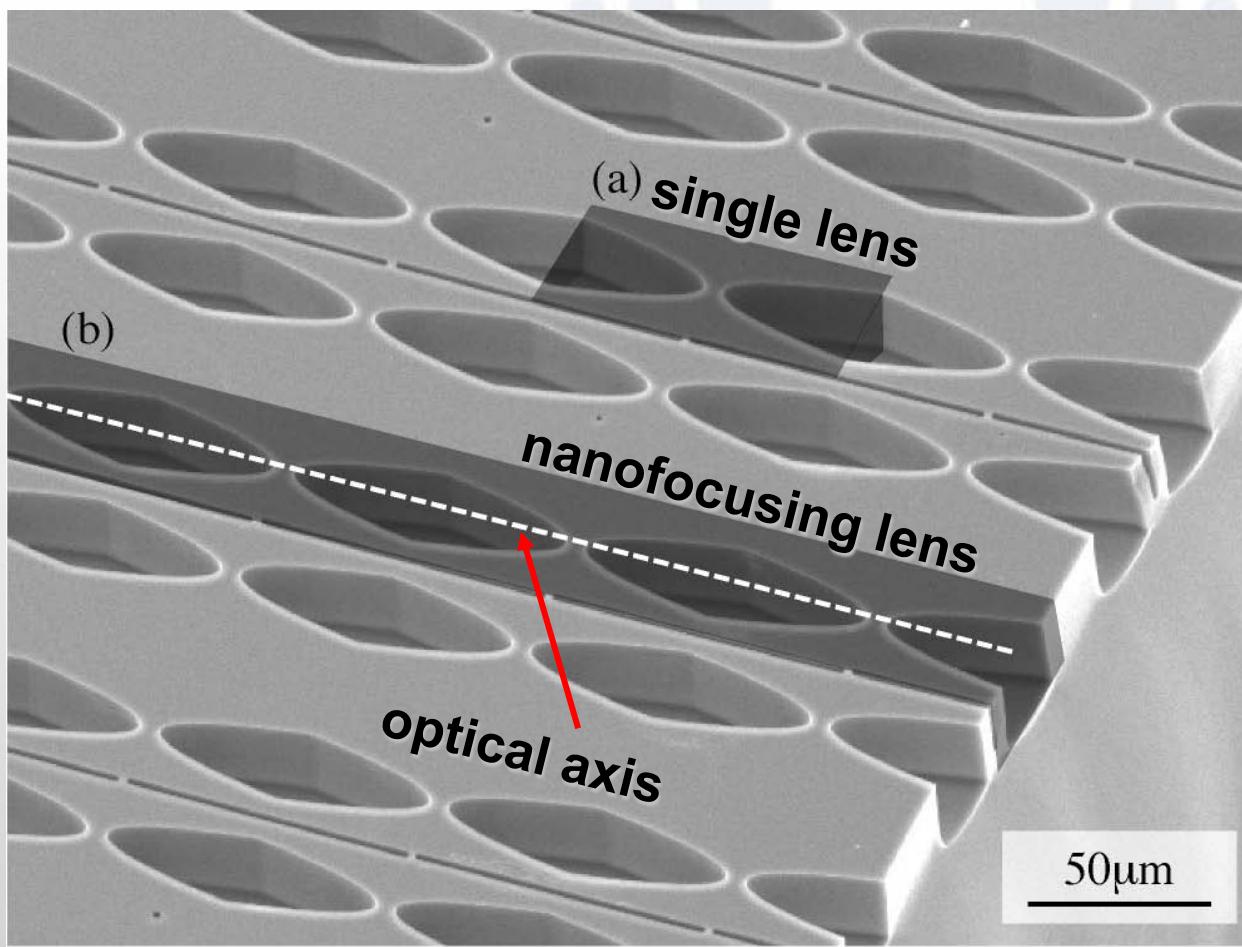
Materials:
**low Z, high
density**
Al, Be, B, Si, ...



C. David et al.
PSI, Villigen, Switzerland



B. Lengeler, C. Schroer, M. Richwin,
RWTH, Aachen, Germany



**lens made of Si by e-beam lithography and
deep trench reactive ion etching**

C. Schroer *et al*, *Applied Physics Letters*, 82(9), 2003

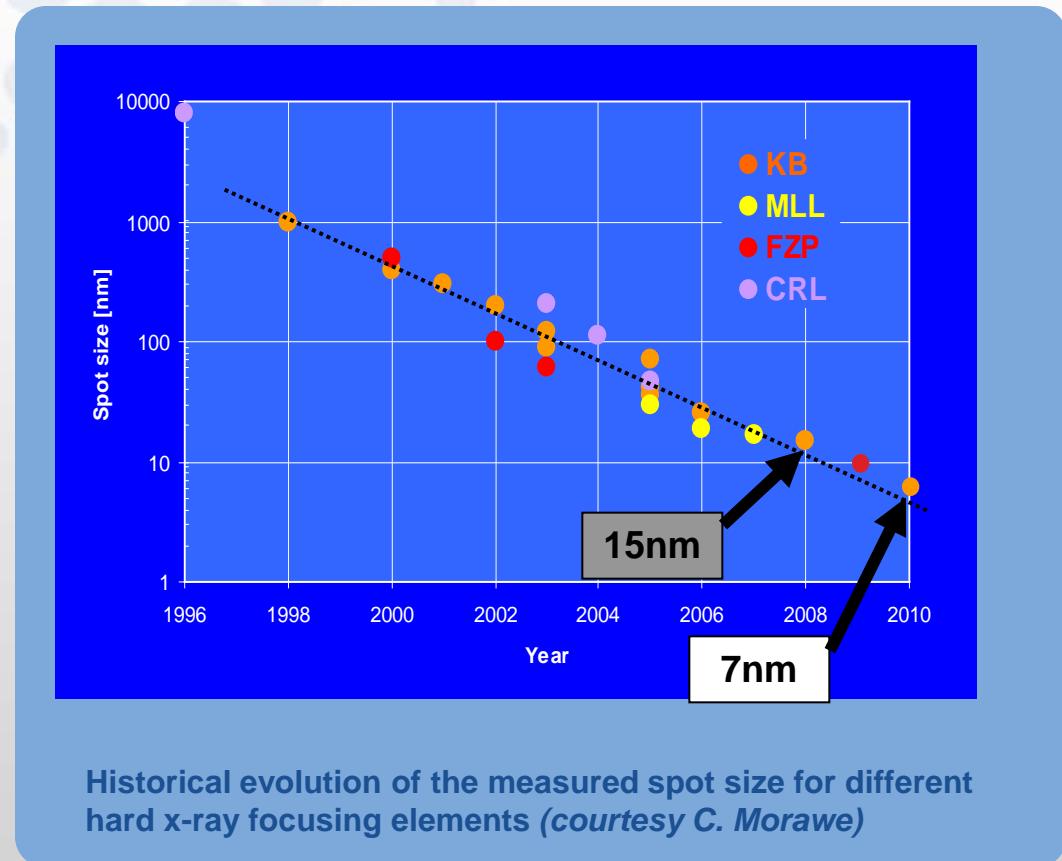
Moore's law adapted to the X-ray world:

**ESRF Red Book (1987):
very few beamline projects
aiming even for 10 micron
sized beams**

**Now optics ~~realistically~~
~~aiming~~ for 10nm beams**

**Routine application of sub-
micron beams still
complicated**

**Also many engineering
issues in implementing
stable, reliable X-ray
nanofocusing systems**



Historical evolution of the measured spot size for different hard x-ray focusing elements (courtesy C. Morawe)

- H. Mimura *et al.* *Nature Physics*, **6**, 122-125 (2010).
- J. Vila-Comamala *et al.*, *Ultramicroscopy*, **109**, 1360–1364 (2009)
- H. Kang *et al.*, *Physical Review Letters*, **96**:127401 (2006)
- C. Schroer *et al.*, *Physical Review Letters*, **94**:054802 (2005)

{ Best focus
Experiments

Ultimate resolution
Theory

The advent of 3rd generation synchrotron X-ray sources has encouraged the development of new X-ray optics

- dramatic improvement in manufacturing and preparation techniques
 - low roughness, high-accuracy figuring, perfect crystals (Ge, Si), diamond, ...
- improved power management strategies
- focusing optics (spot size ~ 50- 0.01μm)
 - zone-plate and refractive lenses, elliptically figured mirrors (Bragg-Fresnel lenses, capillaries, wave guides)
- wide range of experimental requirements – no one ideal optic

R&D programs continuously in progress: current hot-topics

- preservation of the wave-front quality – especially important for anticipated use of fully coherent XFEL sources
- sub-10nm focusing

■ General books and reviews

- **X-ray science and technology** edited by A.G. Michette and C.J. Buckley (King's College London), Institute of Physics Publishing, (1993)
- **Soft X-ray Optics** by E. Spiller SPIE Engineering Press, ISBN 0-8194-1655-X, (1994)
- **Gratings, Mirrors and Slits (*Beamline design for Soft X-ray Synchrotron Radiation Sources*)** by W. B. Peatman, Gordon and Breach Science Publishers, ISBN 90-5699-028-4, (1997)
- **Soft X-rays and extreme ultraviolet radiation; Principles and Applications** by D. Attwood, Cambridge University Press, ISBN 0-521-65214-6, (1999)
- **Third Generation Hard X-ray Synchrotron Radiation Sources, “Source properties, Optics and Experimental techniques”**, edited by D. Mills, Wiley & Sons, ISBN 0-471-31433-1, (2002)
- **Modern Developments in X-ray and Neutron Optics** edited by A. Erko, M. Idir, T. Krist, A.G. Michette, Springer, ISBN 978-3-540-74560-0

■ Selected Publications

- **X-ray Interactions with Matter**
J. Kirz et al. *Quarterly Reviews of Biophysics*, **28**:33130 (1995)
- **Best focus experiments**
H. Mimura et al. *Applied Physics Letters*, **90**:051903 (2007)
- **W. Chao et al., Nature**, **435**:1210 (2005)
- **Ultimate Resolution Theory**
H. Kang et al., *Physical Review Letters*, **96**:127401 (2006)
- **C. Schroer et al., Physical Review Letters**, **94**:054802 (2005)